

Nanoscale Quantum Materials

2018 Quantum Science Summer School
(NSF/DOE/AFSOR)

Judy J. Cha
Yale University

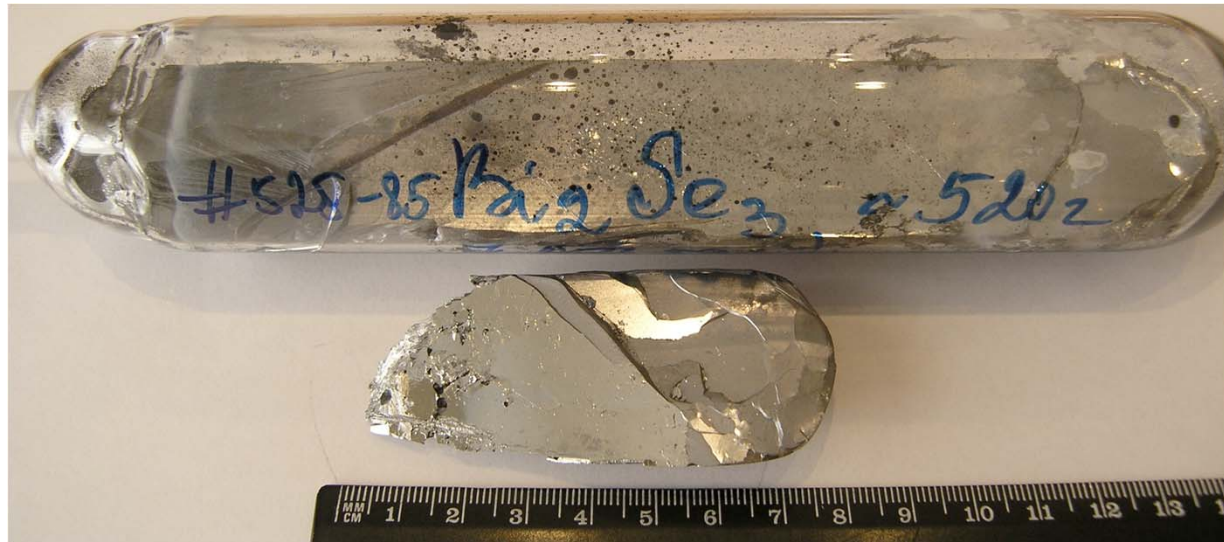
Overview

- Why Nanoscale Materials
 - Emergent properties (band engineering, surface properties)
 - Examples (quantum dots, carbon nanotubes, mechanical properties)
- Synthesis of Nanowires
 - Various growth methods
 - Vapor-liquid-solid growth
 - Doping / surface passivation
- Synthesis of 2D Materials
 - Chemical vapor deposition
 - Precursors / additives

Overview

- Case Study of Nanowires: Si Nanowires
 - Thermal transport modulation
 - Si nanowire batteries
- Case study of topological nanomaterials
 - Bi_2Se_3 topological insulator nanoribbons
 - SnTe Topological crystalline insulator nanowires
- Case study of 2D materials for energy
 - MoS_2 for hydrogen evolution reaction (HER)
 - Phase transition via intercalation and consequences for HER

Topological Materials: Pick Your Favorite!



<http://www.issp.ac.ru/lpcbc/DANDP/Bi-Ch.html>

Explosion of Topological Materials

2007: CdTe/HgTe/CdTe quantum wells to show topological edge states (Science, Molenkamp)

2009: $\text{Bi}_{1-x}\text{Sb}_x$ alloy (Science, Princeton)

2009: Bi_2Se_3 , Bi_2Te_3 , Sb_2Te_3 Topological Insulators (Nature Phys, Nature, Science, Stanford)

2010: Half Heusler compounds: LnPtSb, LnPtBi, LnPdBi, (Nat. Mater, Max Planck)

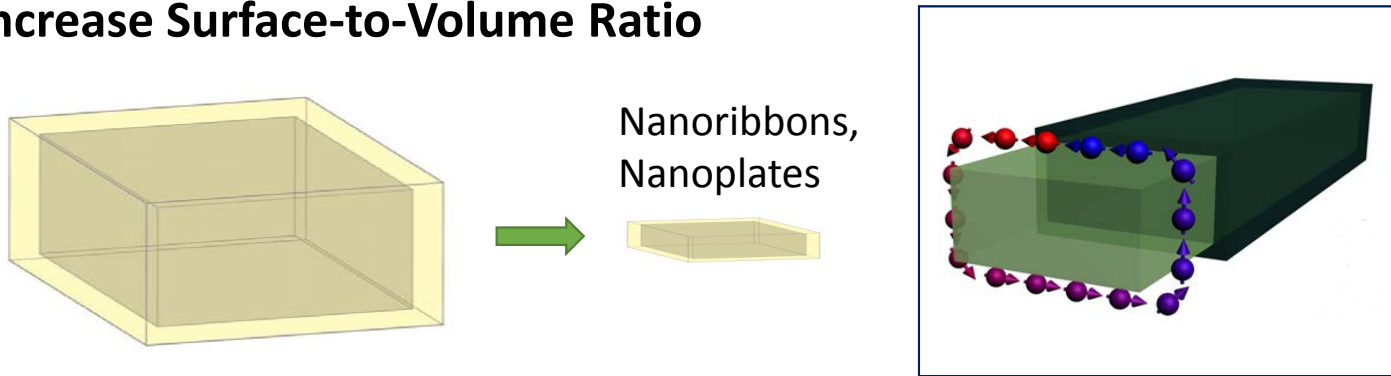
2011: SnTe Topological Crystalline Insulators (Nat. Phys, Experimental Verification 2012, MIT)

2011: Weyl Semimetals (PRL, Experimental Verification 2015 Science): WTe_2 , TaAs, ...

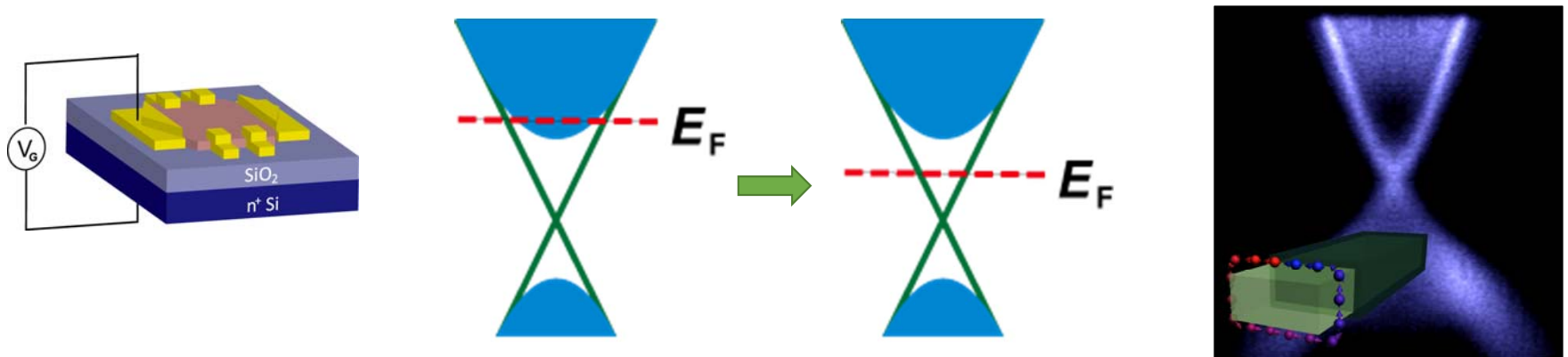
2014: Monolayer transition metal dichalcogenides (2014 Science theory): $1\text{T}'\text{-MoS}_2$...

Nanostructure Approach to Study Topological Insulators

Increase Surface-to-Volume Ratio



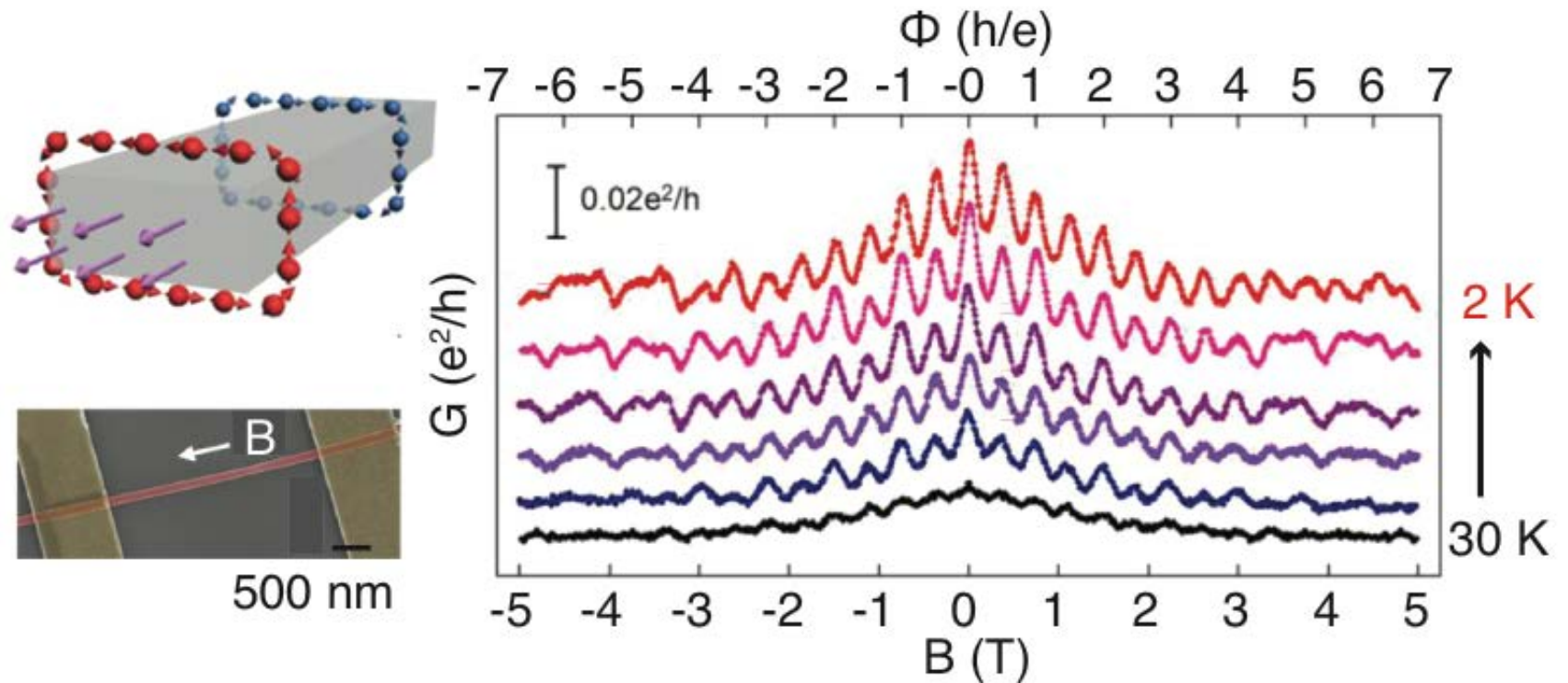
Manipulate Fermi Energy by Gating



Nature Nanotech. 6, 705 (2011); Nano Lett. 14 2815 (2014)

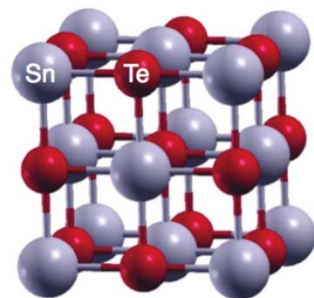
1D Nanowire Interferometer

Aharonov Bohm oscillations in Bi_2Se_3 nanoribbons

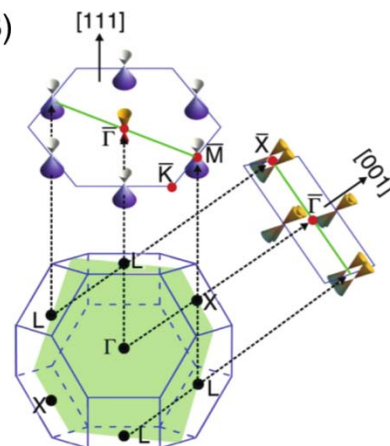


SnTe: Topological Crystalline Insulator

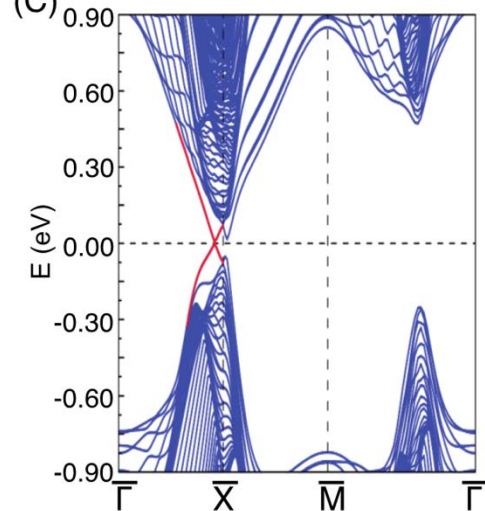
(A)



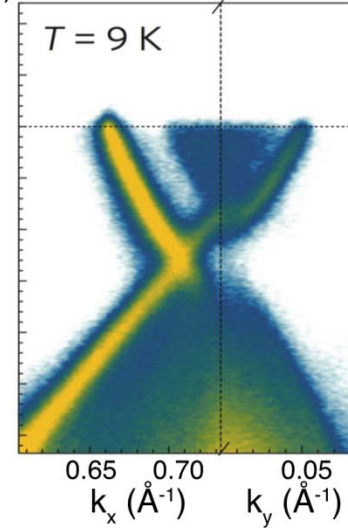
(B)



(C)

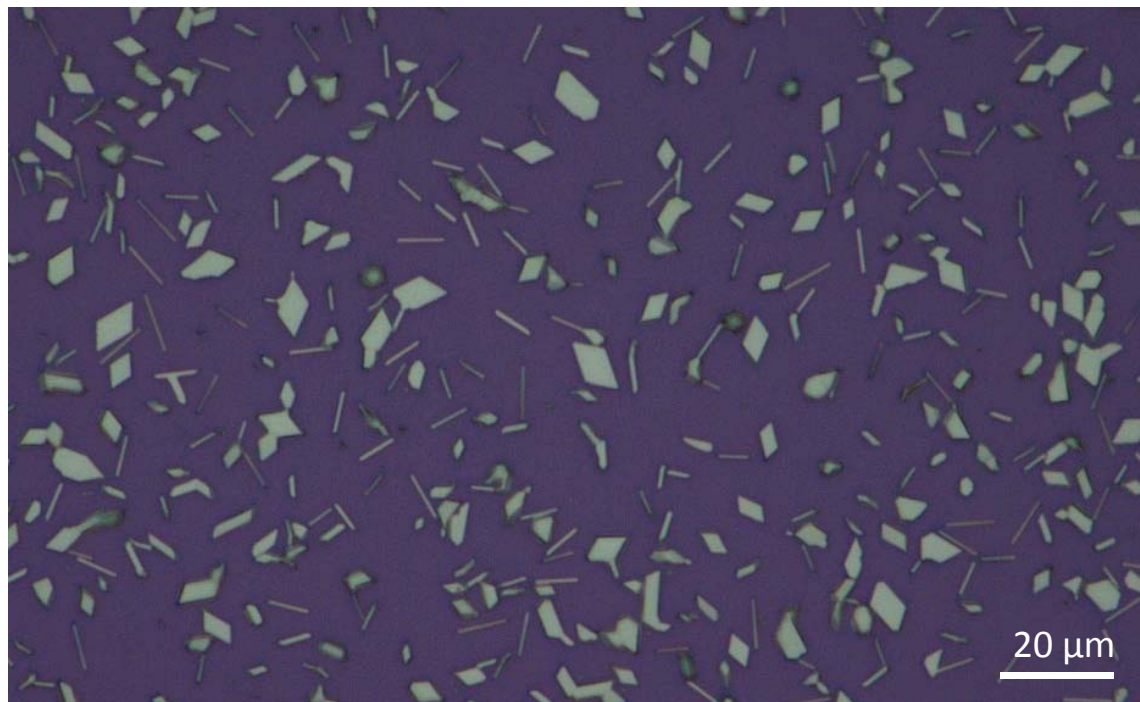
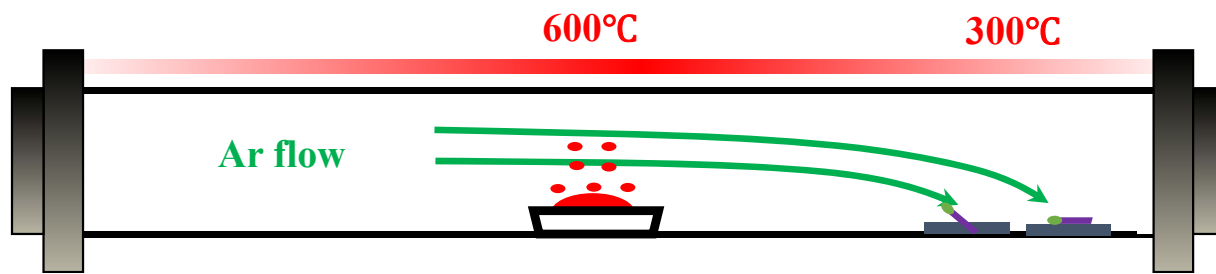


(D) $\bar{\Gamma} \leftarrow \bar{X} \rightarrow \bar{M}$



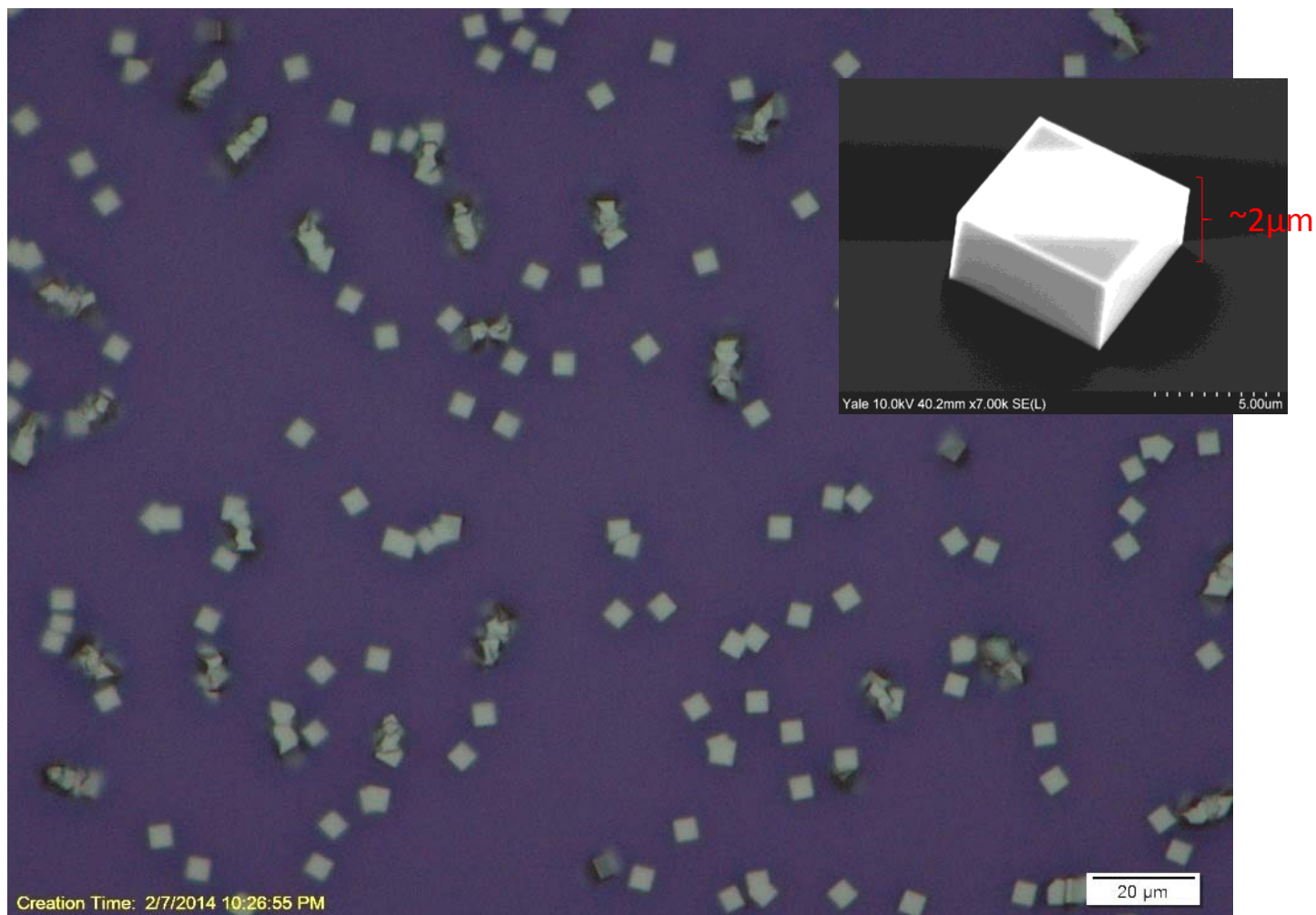
References:
Nat. Commun. 3:982 (2012)
Nat. Mater. 11, 1023 (2012)

SnTe Nanostructure Growth



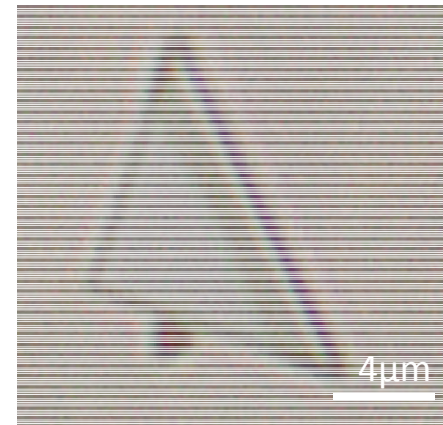
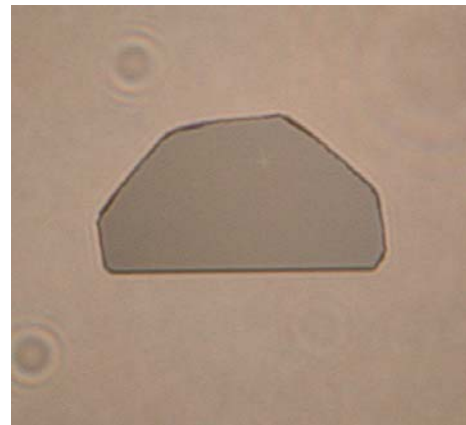
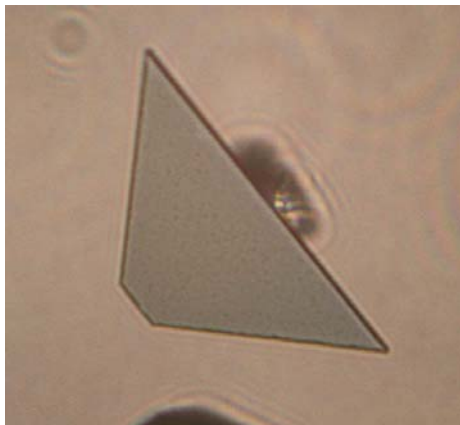
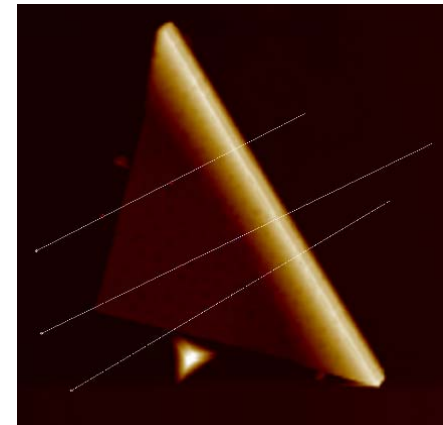
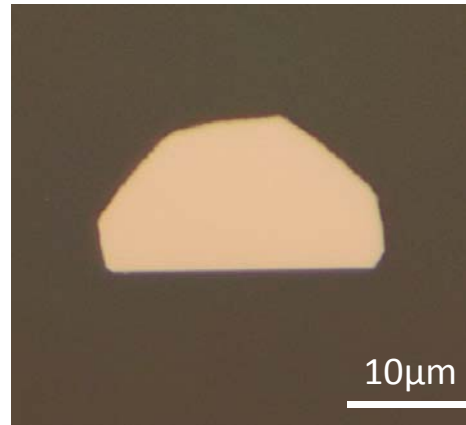
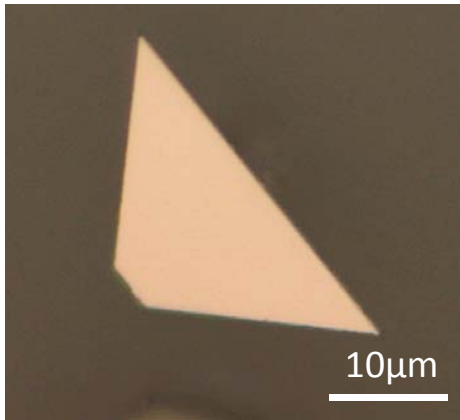
Nano Lett. 14 p.4183 (2014)

SnTe Nanoblocks on SiO₂ without Au Catalyst



Substrate Effects: SnTe grown on Mica

Thickness ~ 40 nm



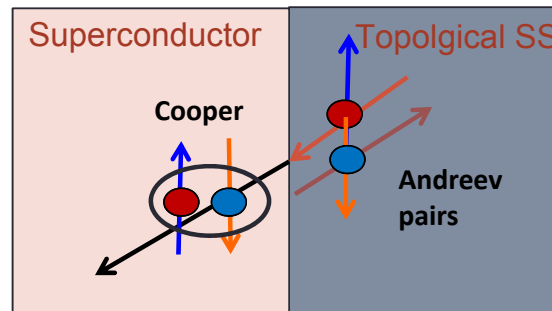
Topological Superconductors (TSCs)

Topological surface states + Superconductor correlations



Potential base system for a quantum information processor

Approach 1: Proximity-induced superconductivity
(Contacting TIs to superconducting metals to induce superconductivity to SS)

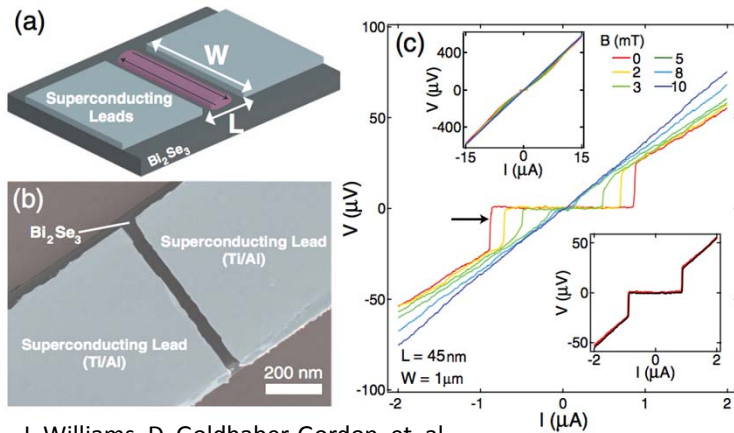


Superconducting proximity effect via Andreev reflection

Approach 2: Directly synthesize a bulk TSC

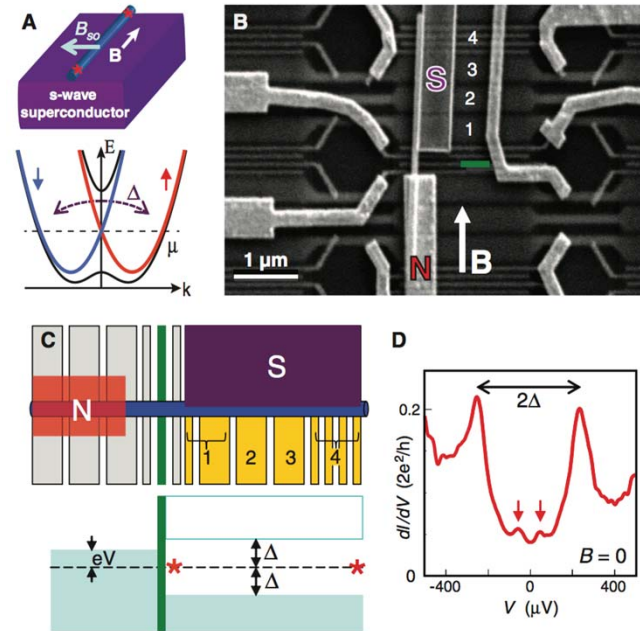
Examples based on Approach 1

TI - SC Josephson junctions



J. Williams, D. Goldhaber-Gordon, et. al.
PRL 109, 056803 (2012)

Semiconducting NW + SC contacts



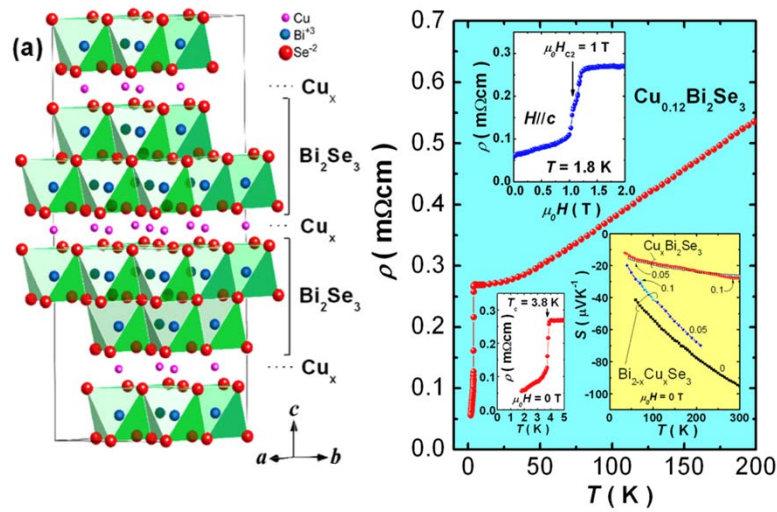
Kouwenhoven et. al., Science 336 p.1003 (2012)

Yazdani et. al., Science 346, p.6209 (2014)

Markus et. al., Nat. Nanotech 10, p.232 (2015)

Approach 2: Make TIs Superconducting

Cu-intercalated Bi_2Se_3

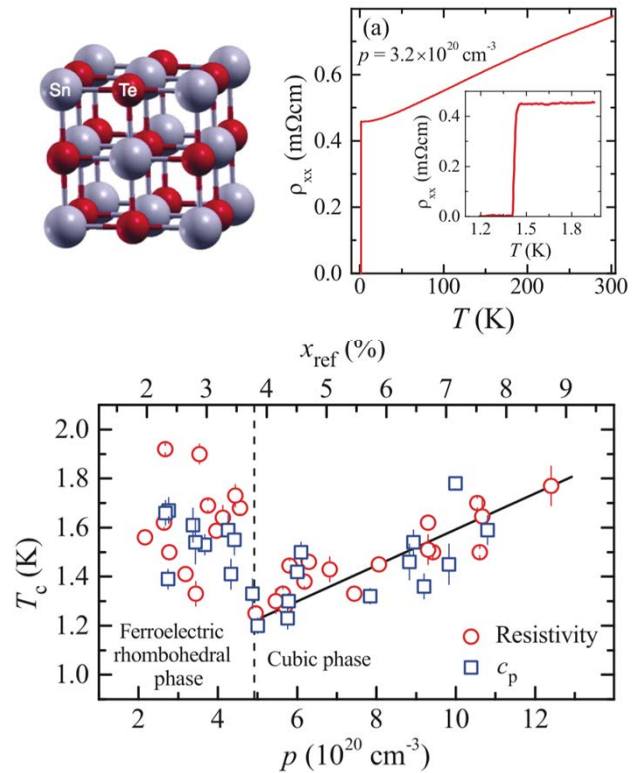


Intercalation: Sr, Tl, ...

PRB 104, 057001 (2010), PRL 107, 217001 (2011)
JACS 137, 10512 (2015), ...

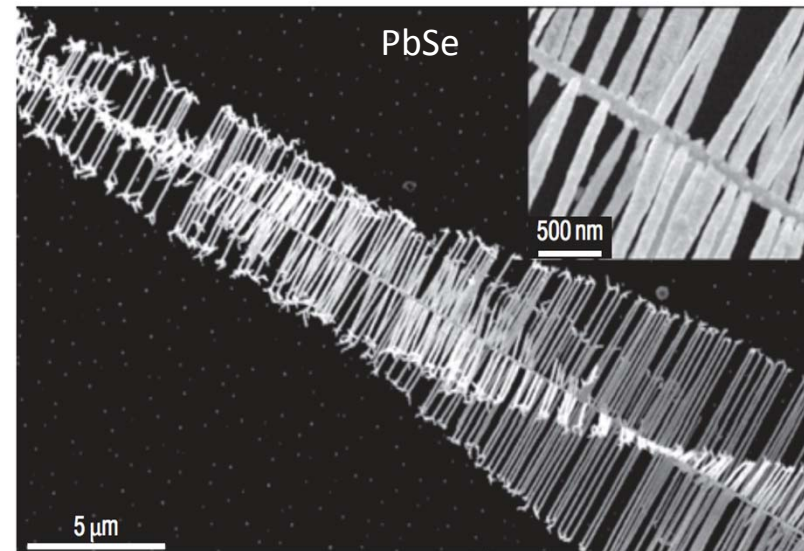
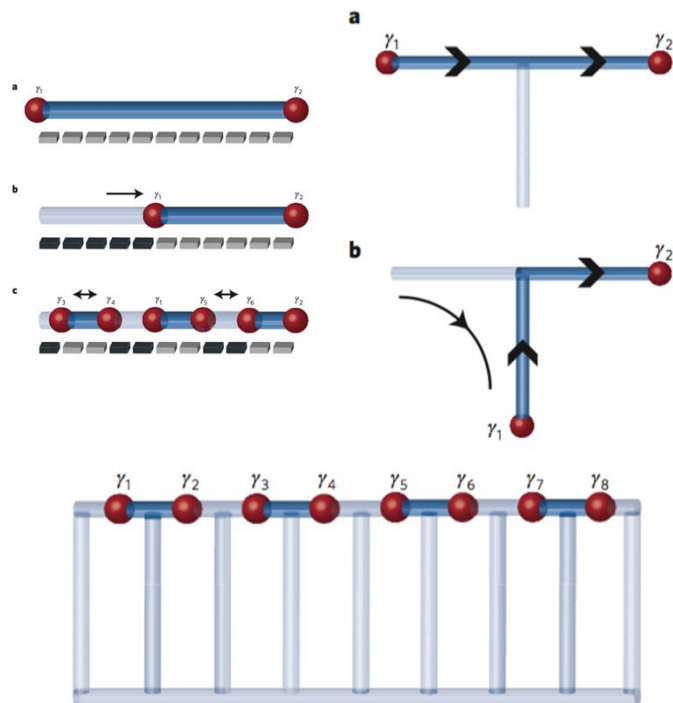
JACS (2012), Nano Lett (2013), Nat. Commun. (2014)

In-doped SnTe



PRB 88, 140502 (2013), PRL 109, 217004 (2012),
PRL 110, 206804 (2013), PRB 93, 024520 (2016), ...

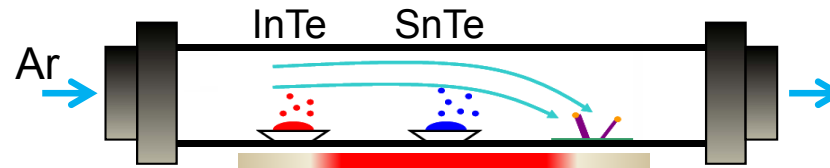
Quantum Processing in 1D Wire Networks



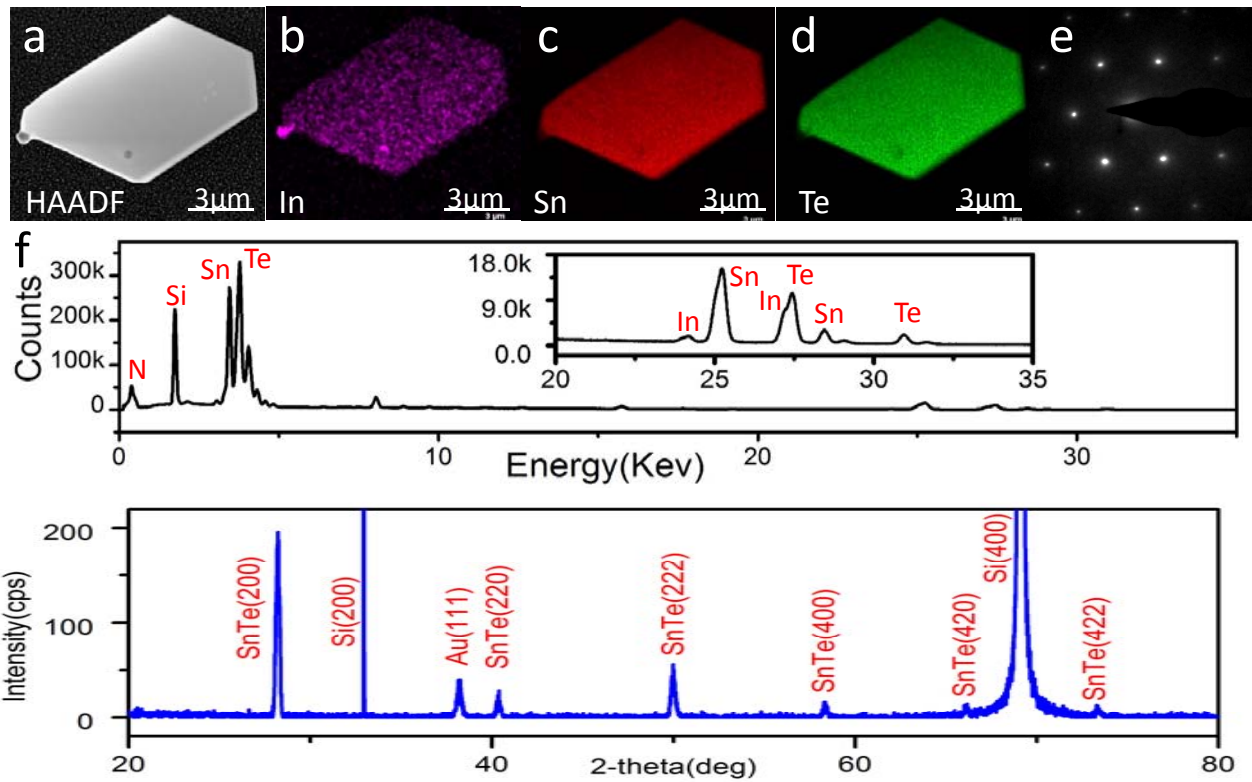
J. Alicea, P. A. Fisher, et. al, Nature Physics 7, 412 (2011)

J. Zhu, Y. Cui, et. al., Nature Nanotech 3, 477 (2008)

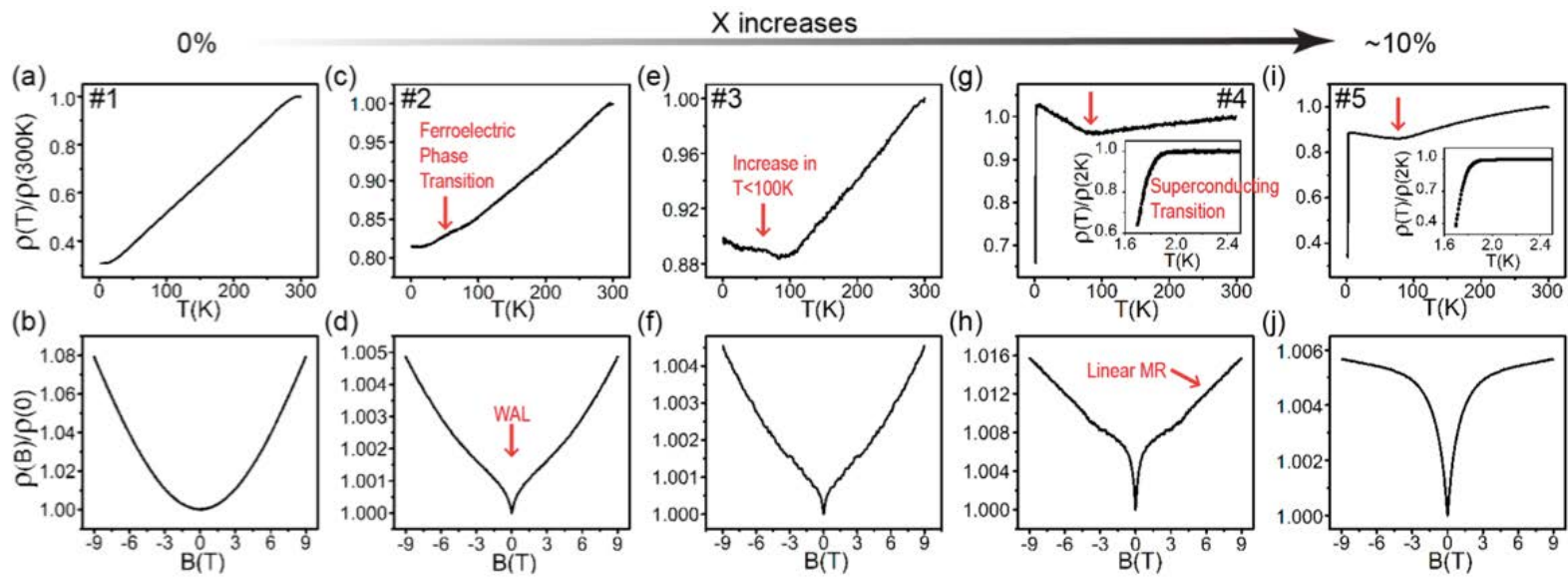
In doping into SnTe Nanoplates



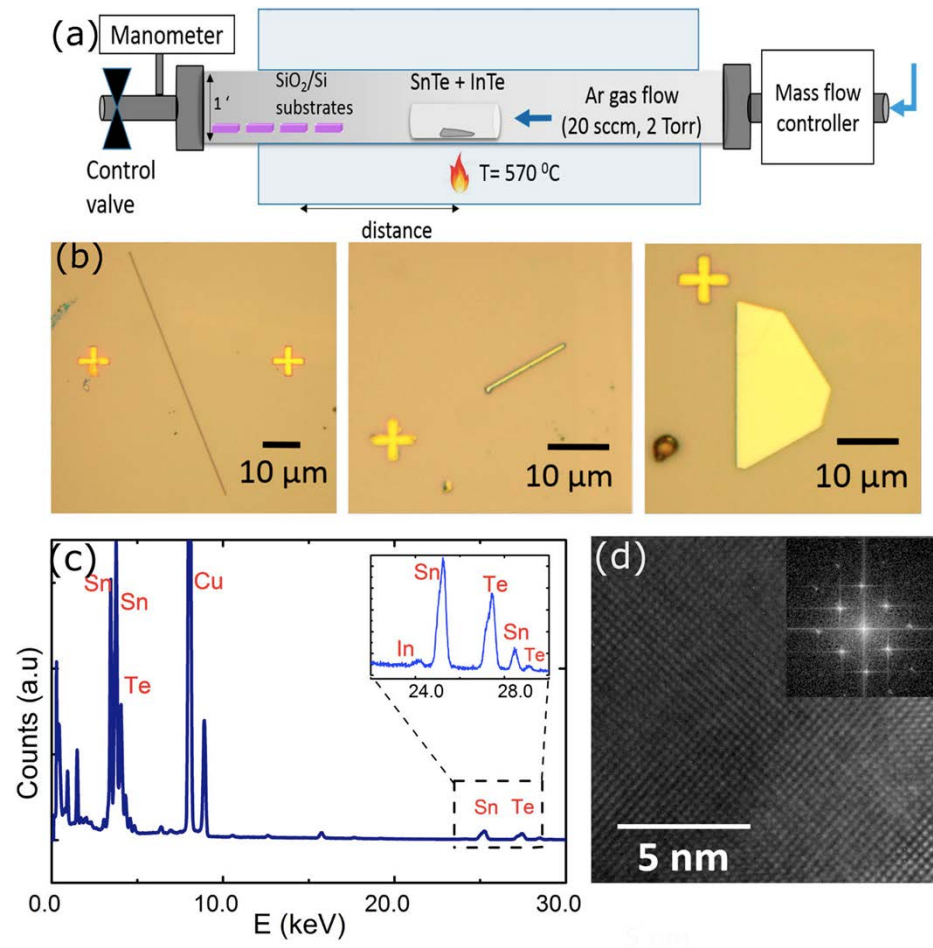
(111) In-doped SnTe Nanoplate



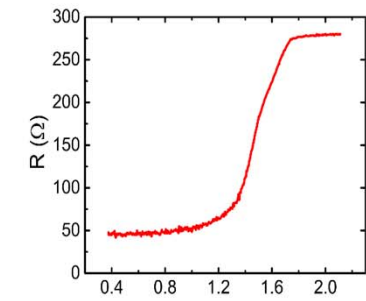
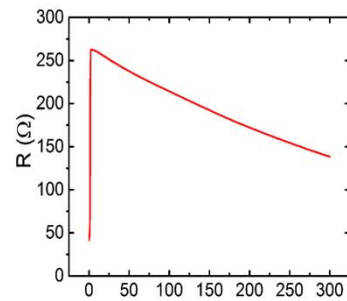
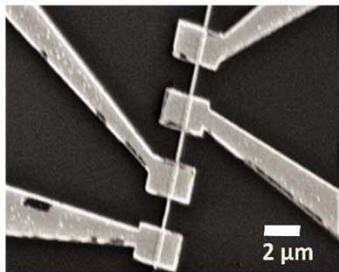
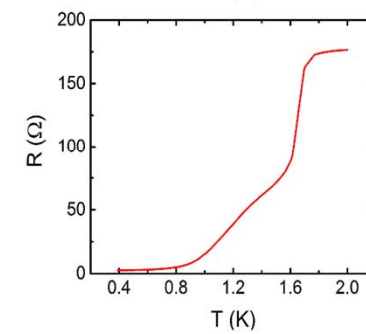
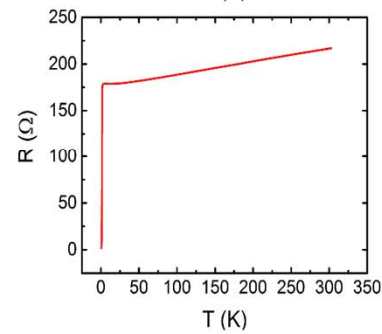
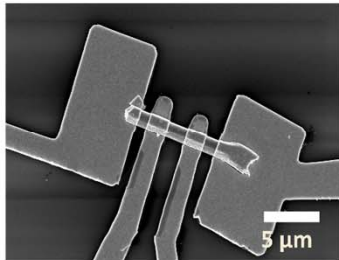
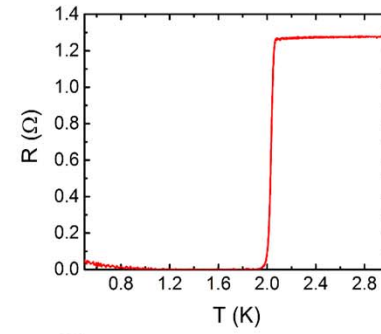
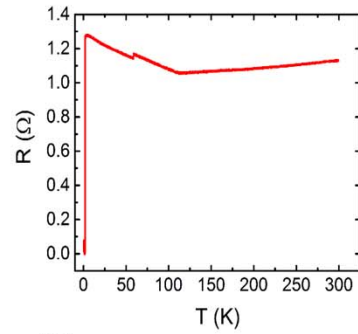
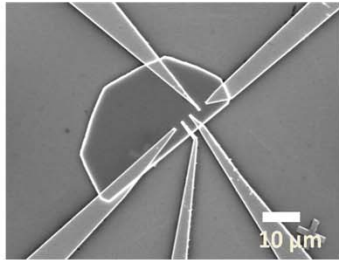
Transport Properties in $\text{In}_x\text{Sn}_{1-x}\text{Te}$



In-doped SnTe Nanowires



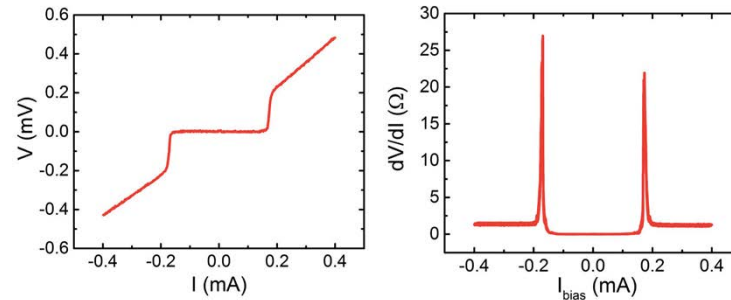
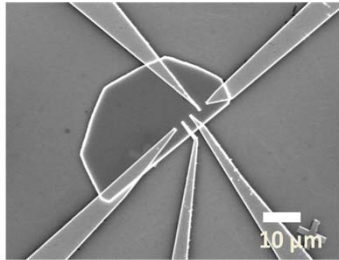
Morphology-dependent Superconducting Behavior



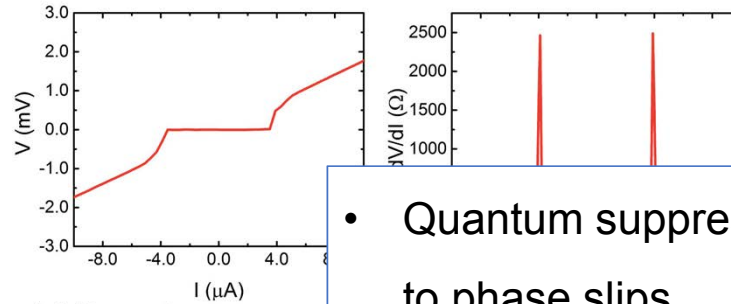
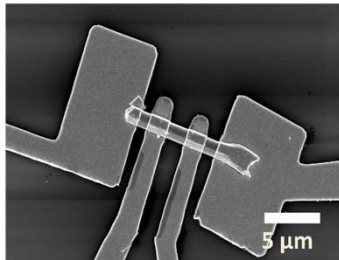
APL Materials 5, 076110 (2017)

Morphology-dependent Superconducting Behavior

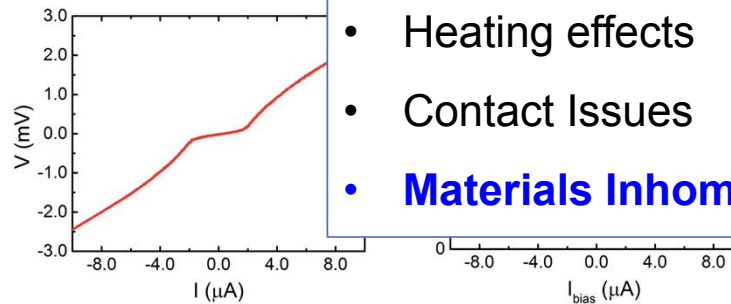
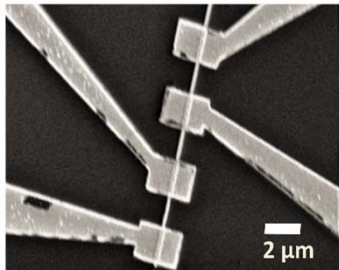
(a) Nanoplate



(b) Nanoribbon

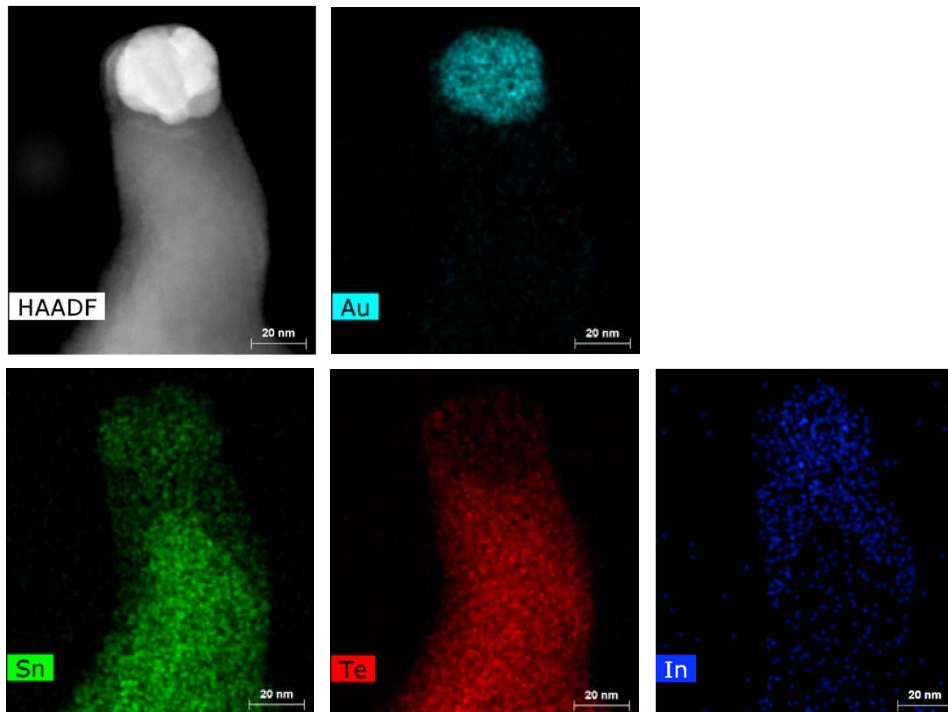


(c) Nanowire

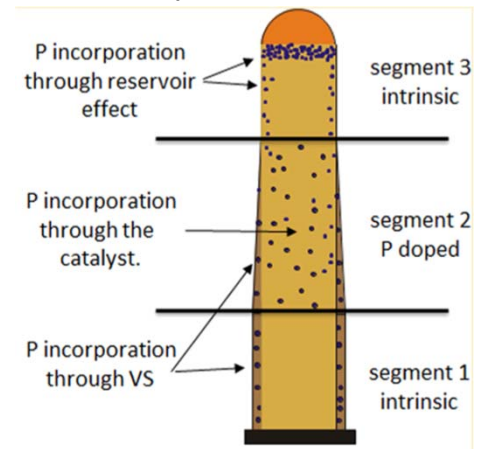


- Quantum suppression due to phase slips
- Heating effects
- Contact Issues
- **Materials Inhomogeneity**

Material Inhomogeneity: In Doping



P-doped Si Nanowires



Nano Lett. 13, 2598 (2013)

Overview

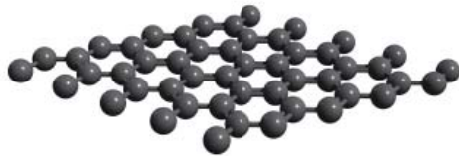
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Why 2D Materials?

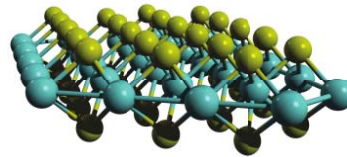
- New Physics
 - Dirac band dispersion in Graphene
- New Materials
 - Graphene, Silicene, ...
- Ultimate thickness in 2D technology
 - Bandgap engineering via thickness
 - Flexible, transparent electronics
 - 2D materials can potentially be integrated into existing CMOS technology

2D Materials Are Interesting

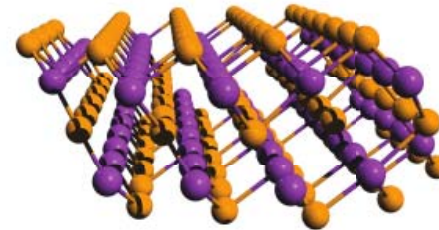
Graphene



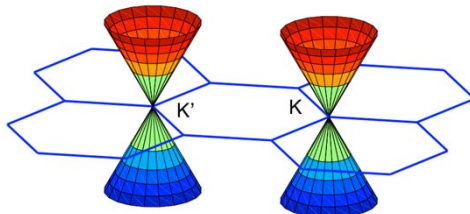
MoS₂



Bi₂Se₃

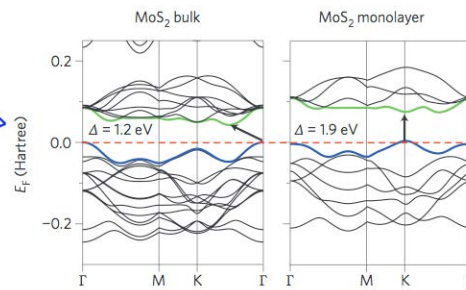


Dirac Physics



- Transparent electrodes
- Conducting layer for energy applications

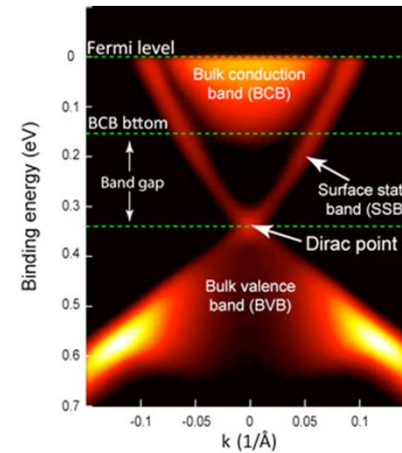
Indirect \rightarrow Direct Semiconductor



PRB 83, 245213 (2011)

- Field-effect transistor
- Hydrogen evolution reaction catalyst

Topological Insulator



Science 329, 659 (2010)

2D Materials Choice

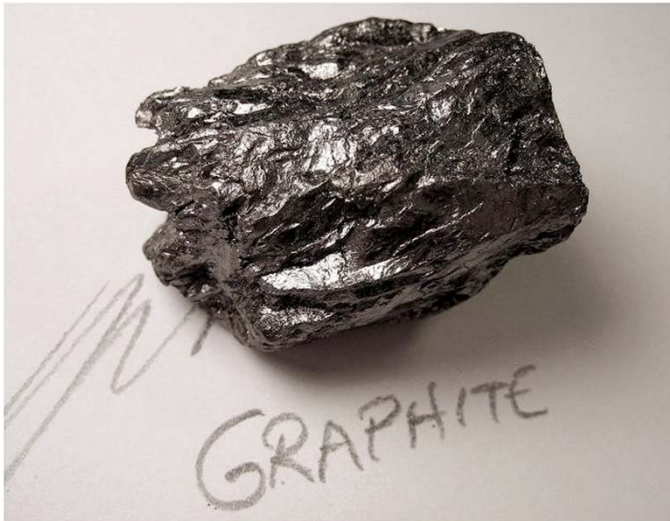
Topological Insulators: Bi_2Se_3 , Bi_2Te_3 , ...

Graphene family	Graphene	hBN 'white graphene'	BCN	Fluorographene	Graphene oxide
2D chalcogenides	MoS_2 , WS_2 , MoSe_2 , WSe_2		Semiconducting dichalcogenides: MoTe_2 , WTe_2 , ZrS_2 , ZrSe_2 and so on	Metallic dichalcogenides: NbSe_2 , NbS_2 , TaS_2 , TiS_2 , NiSe_2 and so on	
				Layered semiconductors: GaSe , GaTe , InSe , Bi_2Se_3 and so on	
2D oxides	Micas, BSCCO	MoO_3 , WO_3	Perovskite-type: LaNb_2O_7 , $(\text{Ca,Sr})_2\text{Nb}_3\text{O}_{10}$, $\text{Bi}_4\text{Ti}_3\text{O}_{12}$, $\text{Ca}_2\text{Ta}_2\text{TiO}_{10}$ and so on		Hydroxides: $\text{Ni}(\text{OH})_2$, $\text{Eu}(\text{OH})_2$ and so on
	Layered Cu oxides	TiO_2 , MnO_2 , V_2O_5 , TaO_3 , RuO_2 and so on			Others

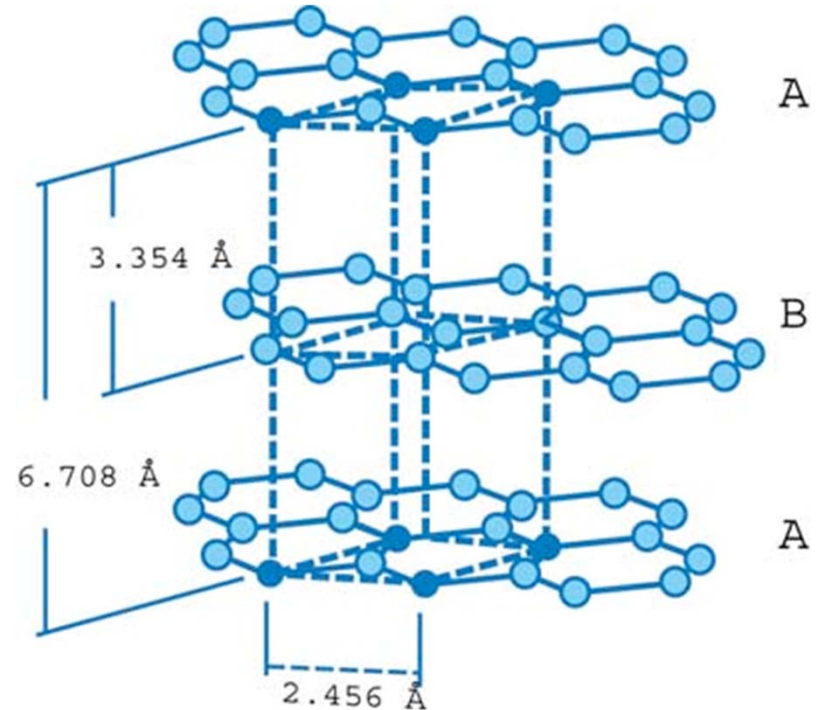
Geim & Grigorieva,
Nature 499, 419–425 (25 July 2013)

Top Down Approach: From Graphite

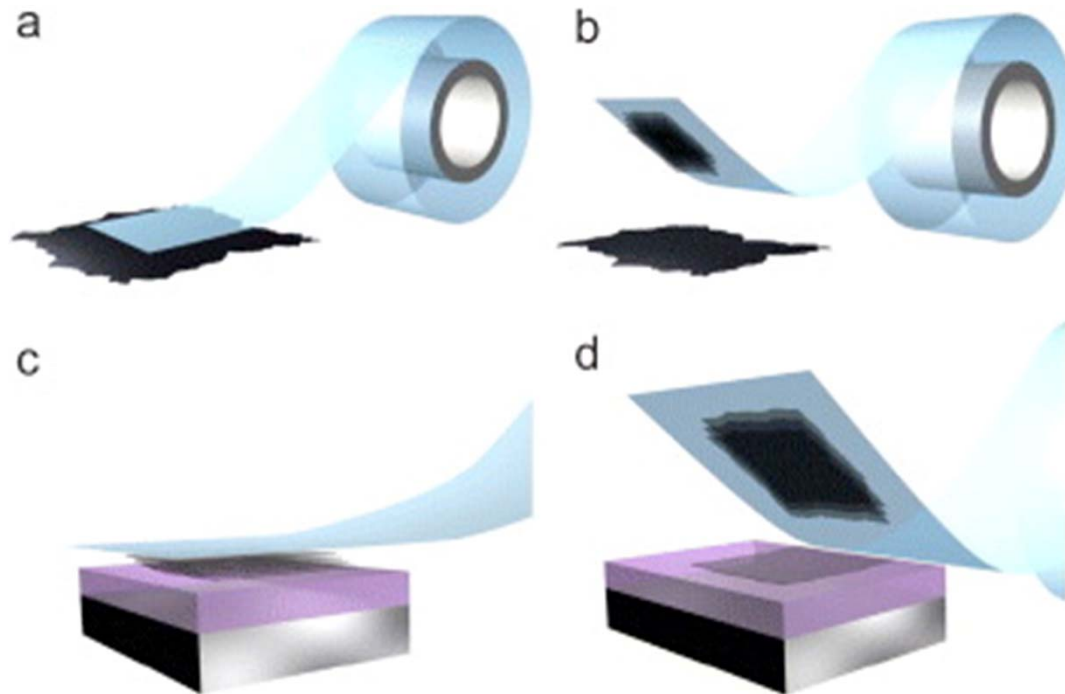
Graphite: Layered Crystal Structure



- Mechanical Exfoliation
- Chemical Exfoliation
- Direct Growth
 - CVD, Evaporation of SiC



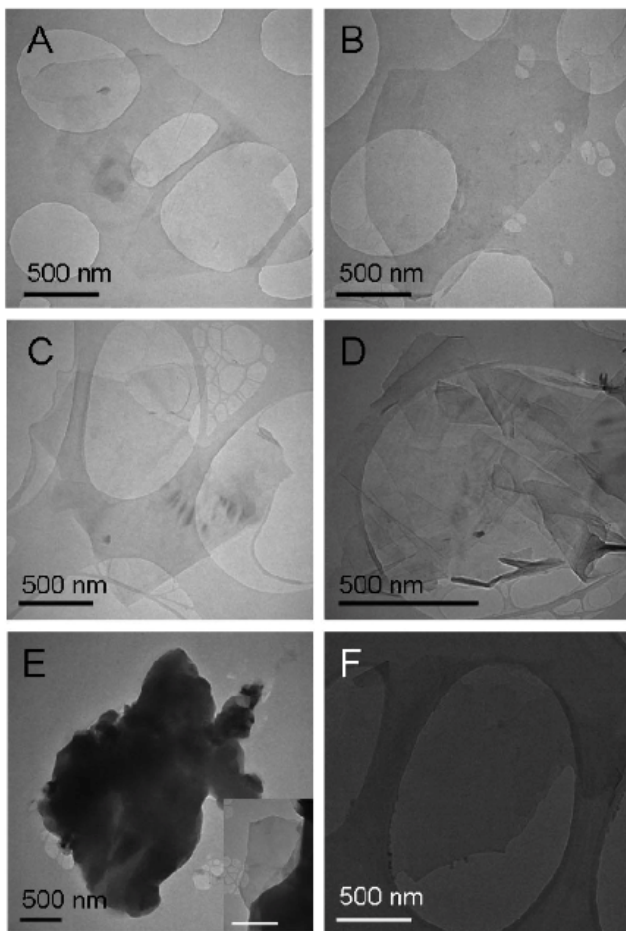
Mechanical Exfoliation



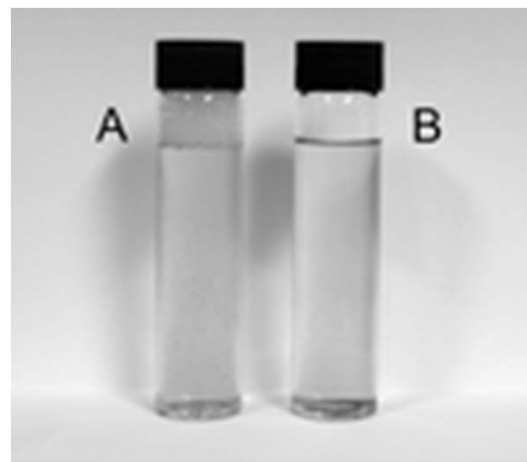
Physica Scripta **2012**, 014006

<http://www.youtube.com/watch?v=waO020l25sU>

Chemical Exfoliation of Graphite

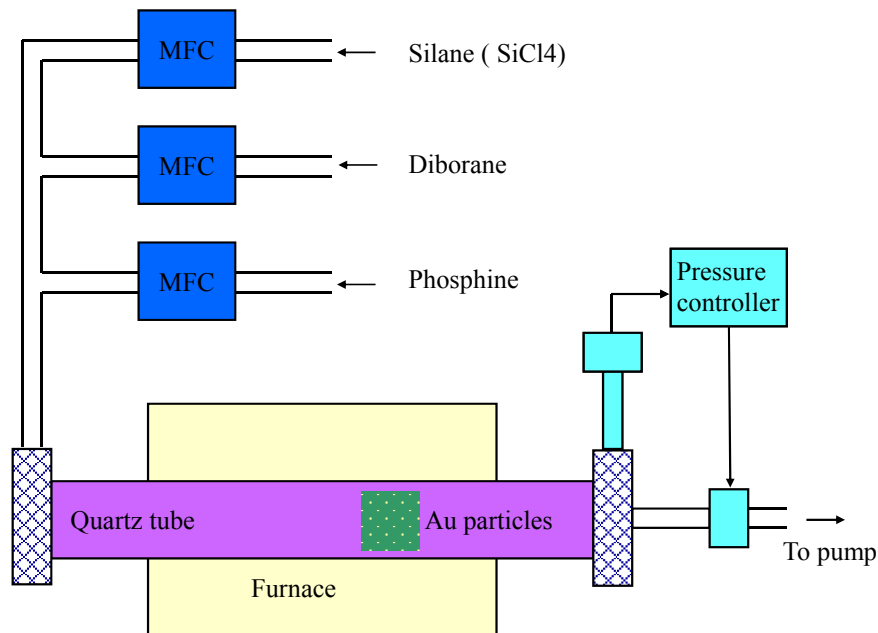
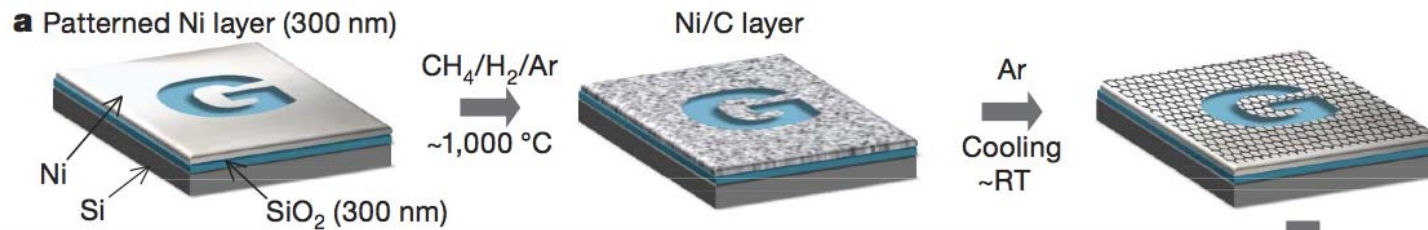


Surfactant-Water Solution



JACS 131, p.3611 (2009)

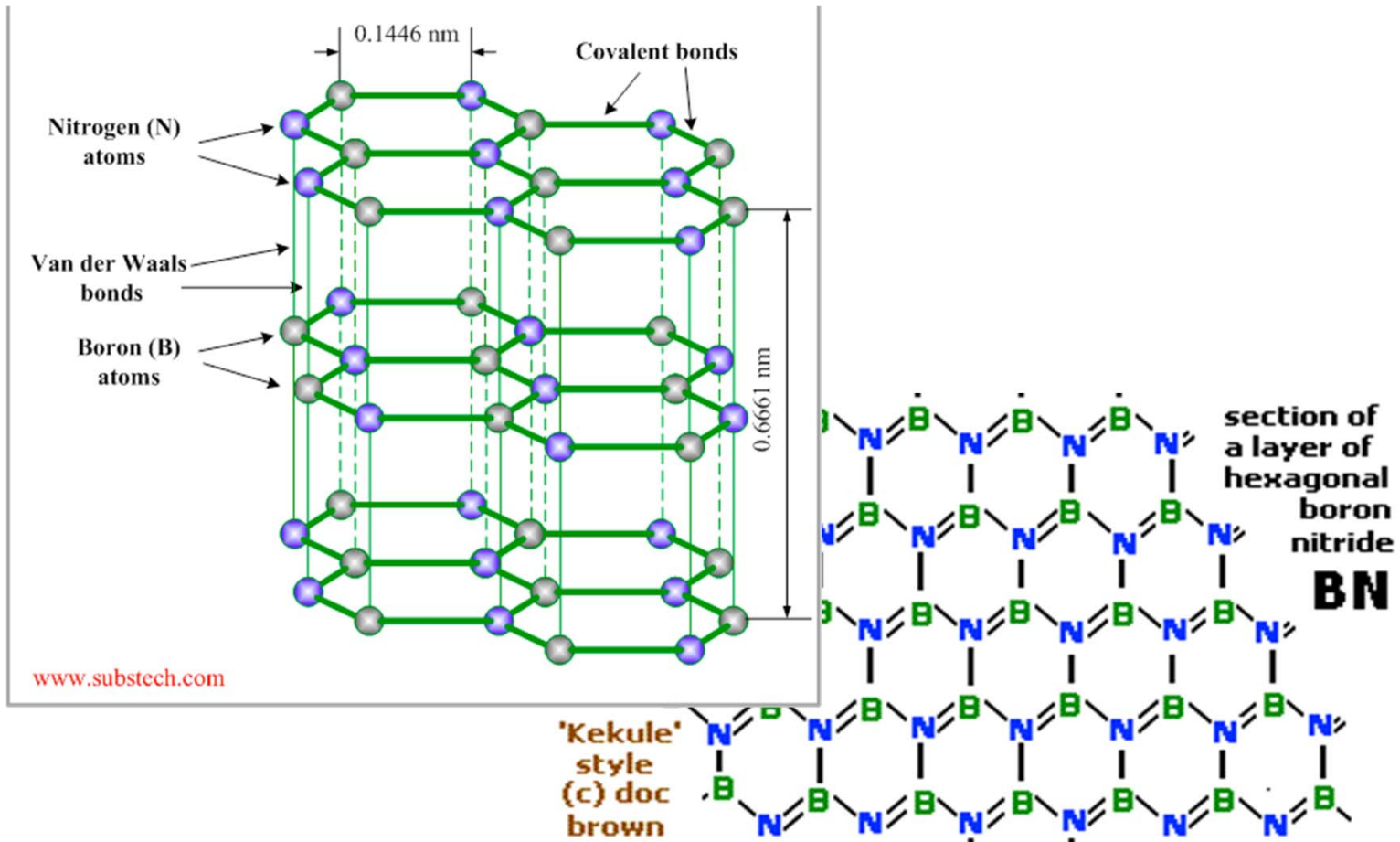
CVD Growth of Graphene



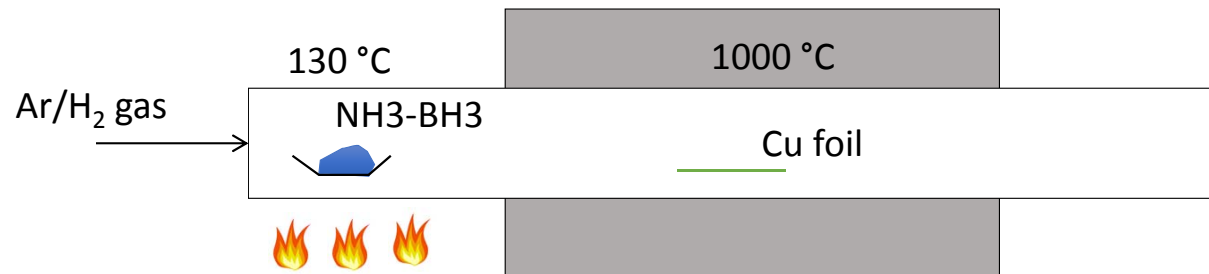
Nature 457, p.706 (2009)

- Cu
- Pt
- Ni
- ...

Hexagonal Boron Nitride

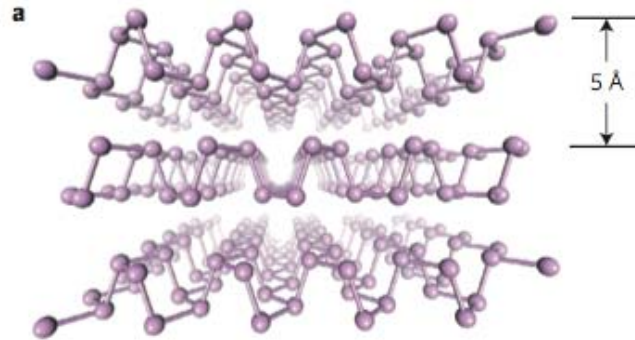


CVD of Boron Nitride



- tube furnace with a fused quartz processing tube.
 - A copper foil with 25 μm thickness was used as substrate.
- 1) The Cu foil was quick washed by nitric acid and deionized water.
 - 2) It was placed in the center of a furnace, annealed at 600 °C for 20 min in Ar/H₂ (15 vol % H₂, 85 vol % argon) flow with 500 sccm.
 - 3) The furnace was gradually heated up to 1000 °C in 40 min.
 - 4) Ammonia borane (NH₃-BH₃) was sublimated at 120–130 °C by using a heating belt and then carried into the reaction region by Ar/H₂ gas glow.
 - 5) During the growth process, Ar/H₂ flow was kept as 200 sccm. The typical growth time is 30–60 min.
 - 6) After growth, the furnace was cooled down to room temperature quickly.

2D, Layered Black Phosphorus

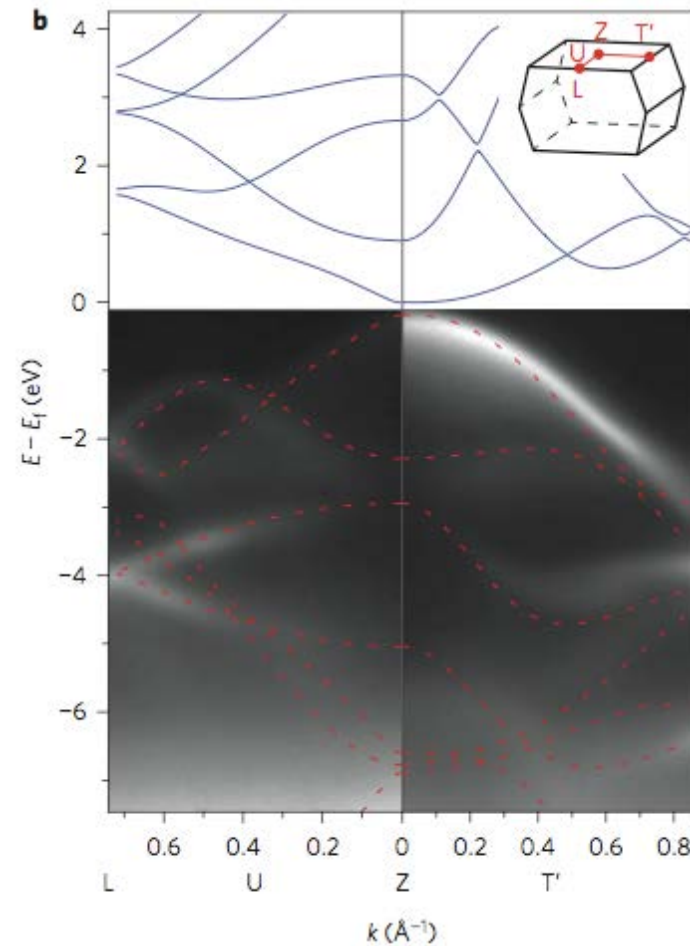


Two atomic sheets of Phosphorus atoms make a sheet.

Unlike graphene, which is a metal (no intrinsic bandgap), BP has a bandgap. In addition, mobility of BP is relatively high.

: $\sim 1,000 \text{ cm}^2/\text{Vs}$

- Not as high as graphene
- But much higher than MoS_2 ($\sim 100 \text{ cm}^2/\text{Vs}$)



Nature Nanotechnology, 9 p.372 (2014)

CVD Growth of Black Phosphorus Thin Film

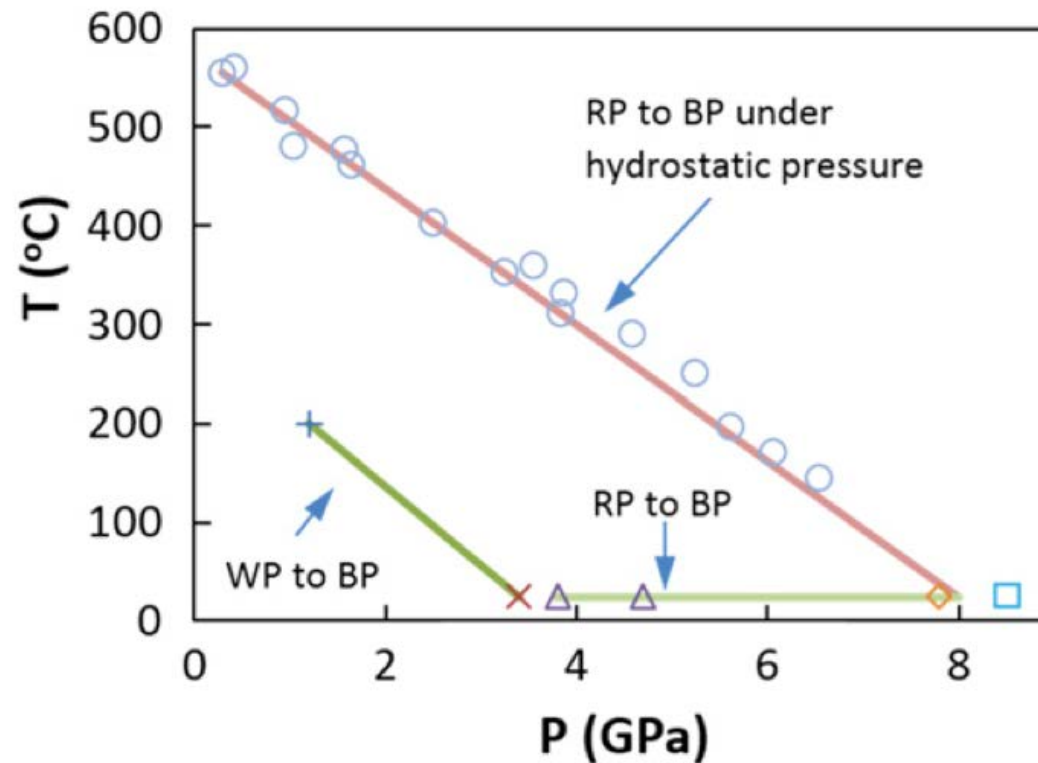
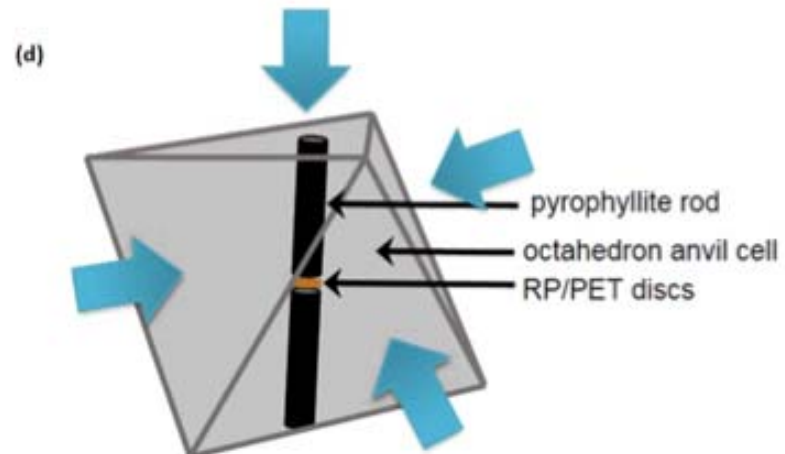
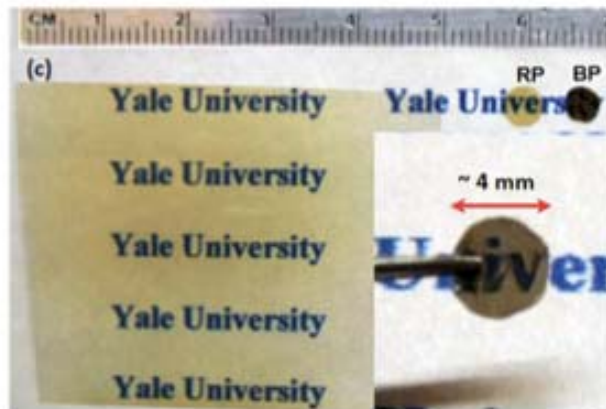
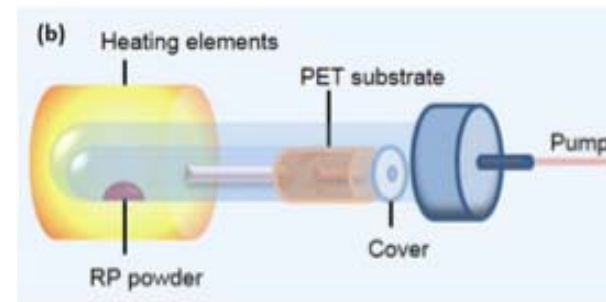
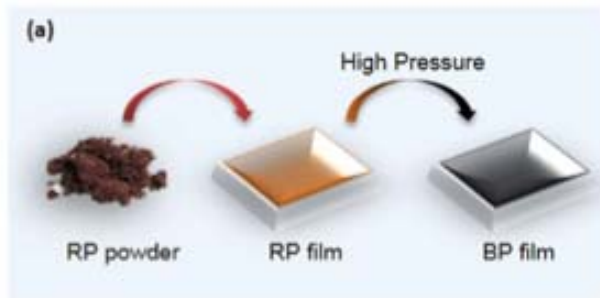


Figure 1. Criteria for the conversion of BP from WP or RP at various pressures and temperatures summarized from the literature: +[14], x[15], △[18, 19], □[16], ◇[17], ○[20].

CVD Growth of Black Phosphorus Thin Film

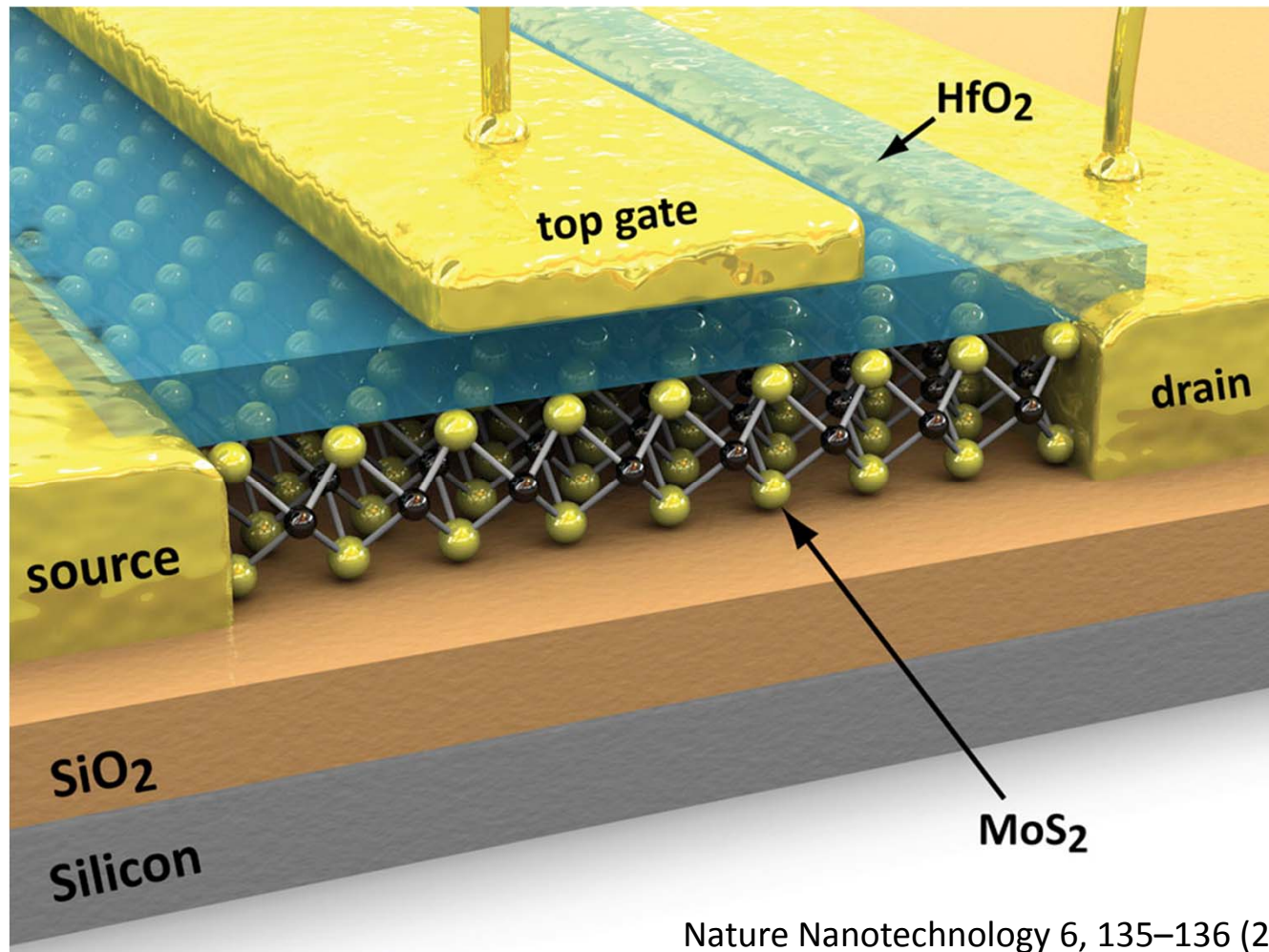


B) Heat red phosphorus powder. At the colder zone, flexible PET (polyethylene terephthalate).

D) Pressurizing Diamond Anvil Cell

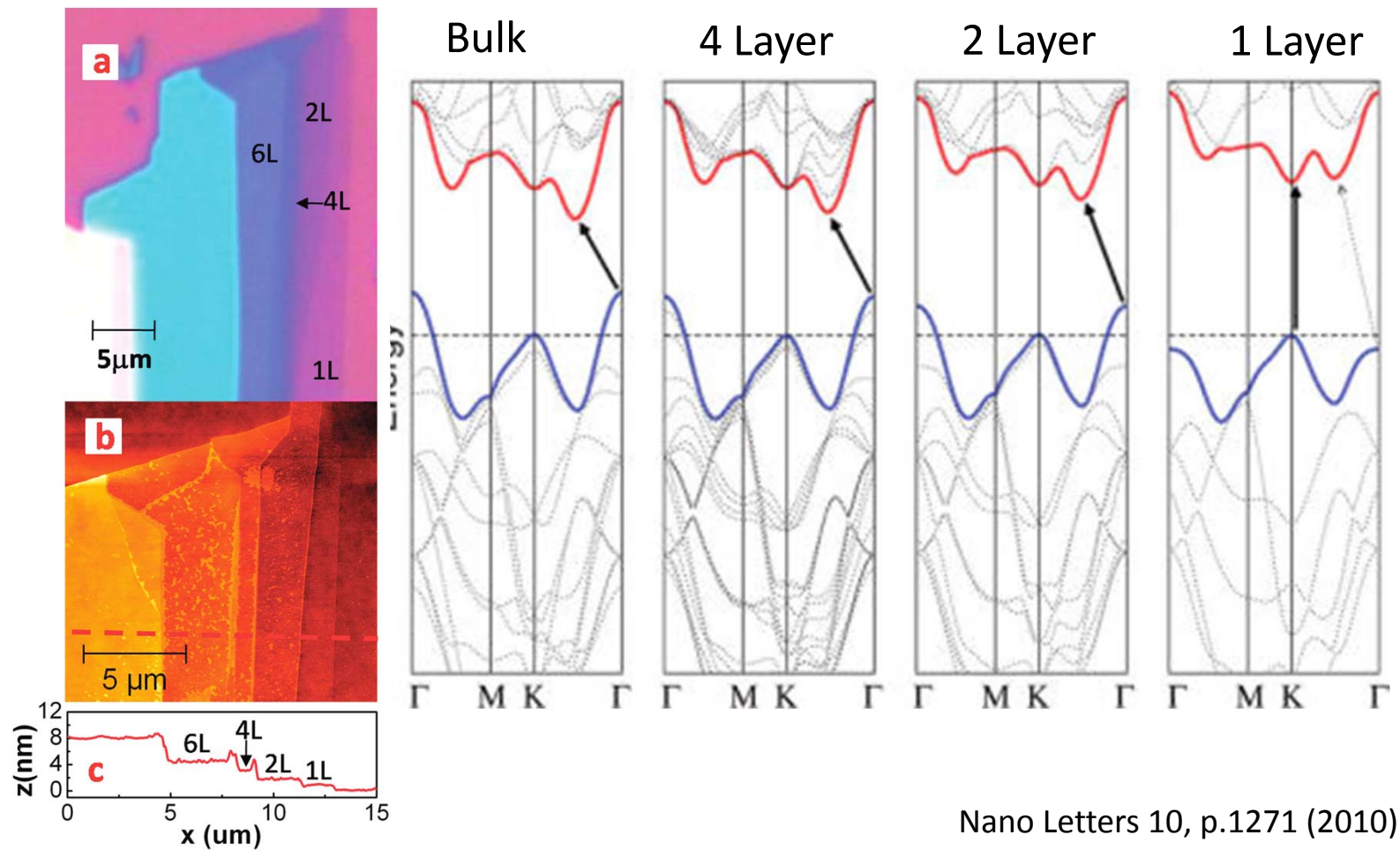
C) Large, converted Black Phosphorus Film

MoS₂

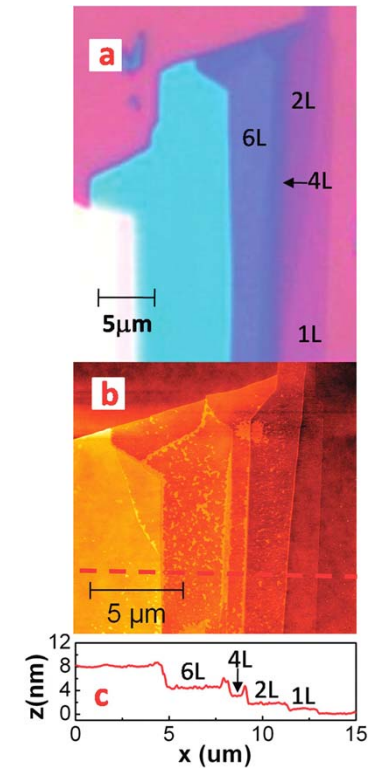
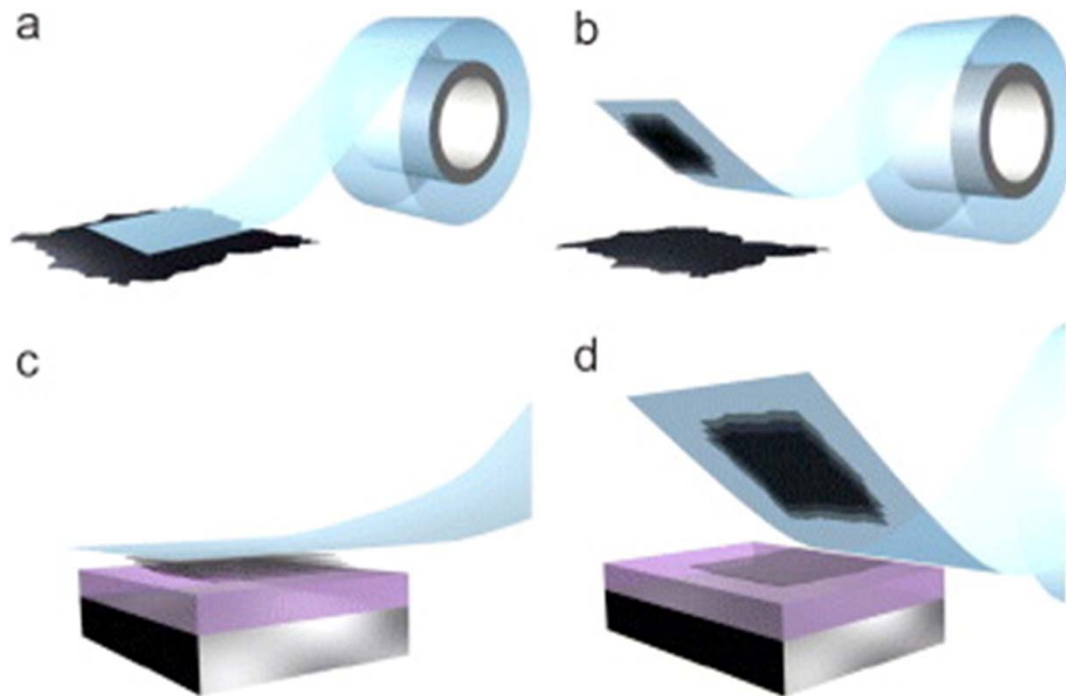


Nature Nanotechnology 6, 135–136 (2011)

MoS₂: Indirect to Direct Semiconductor



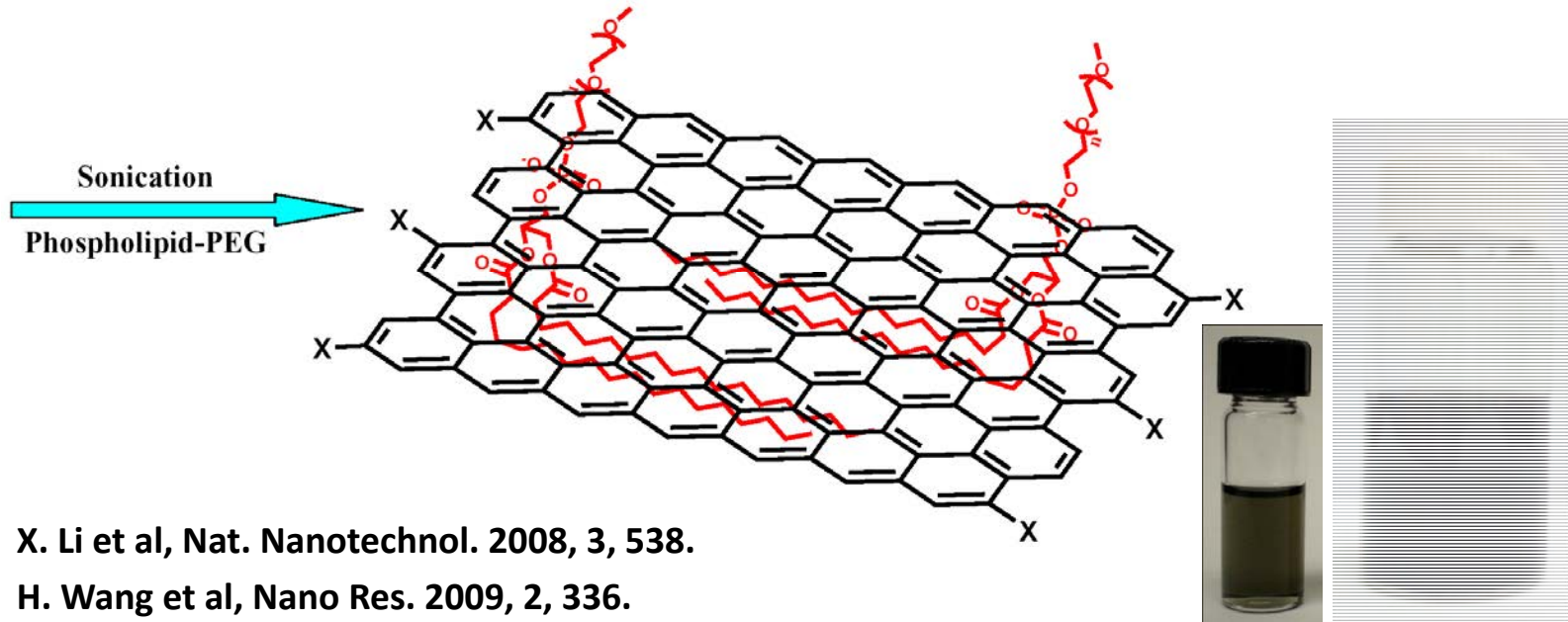
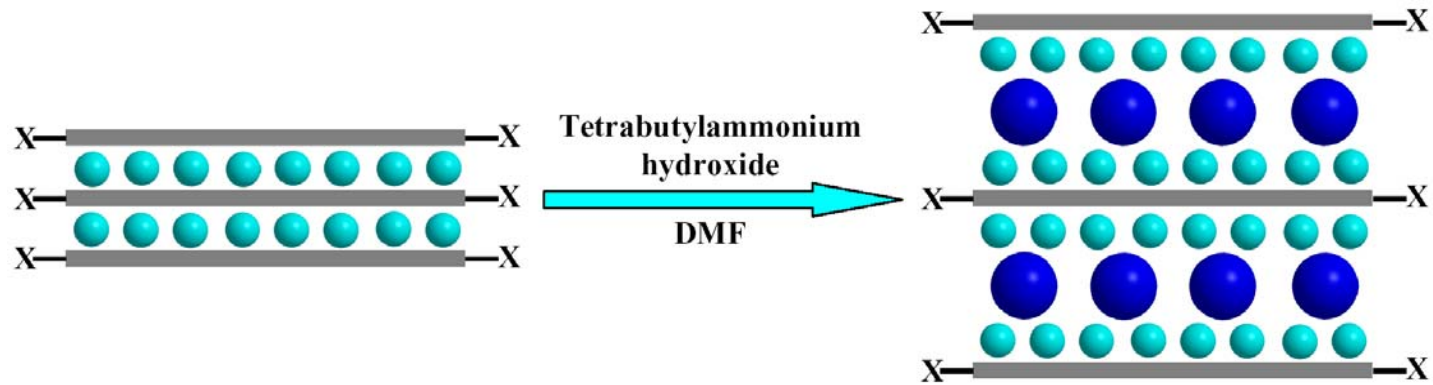
Mechanical Exfoliation



Physica Scripta **2012**, 014006

<http://www.youtube.com/watch?v=waO020l25sU>

Chemical exfoliation

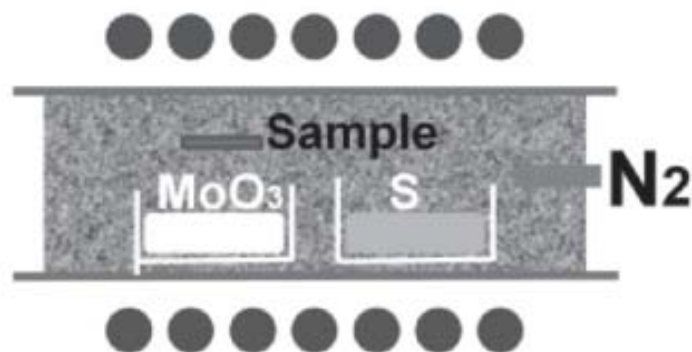


X. Li et al, Nat. Nanotechnol. 2008, 3, 538.

H. Wang et al, Nano Res. 2009, 2, 336.

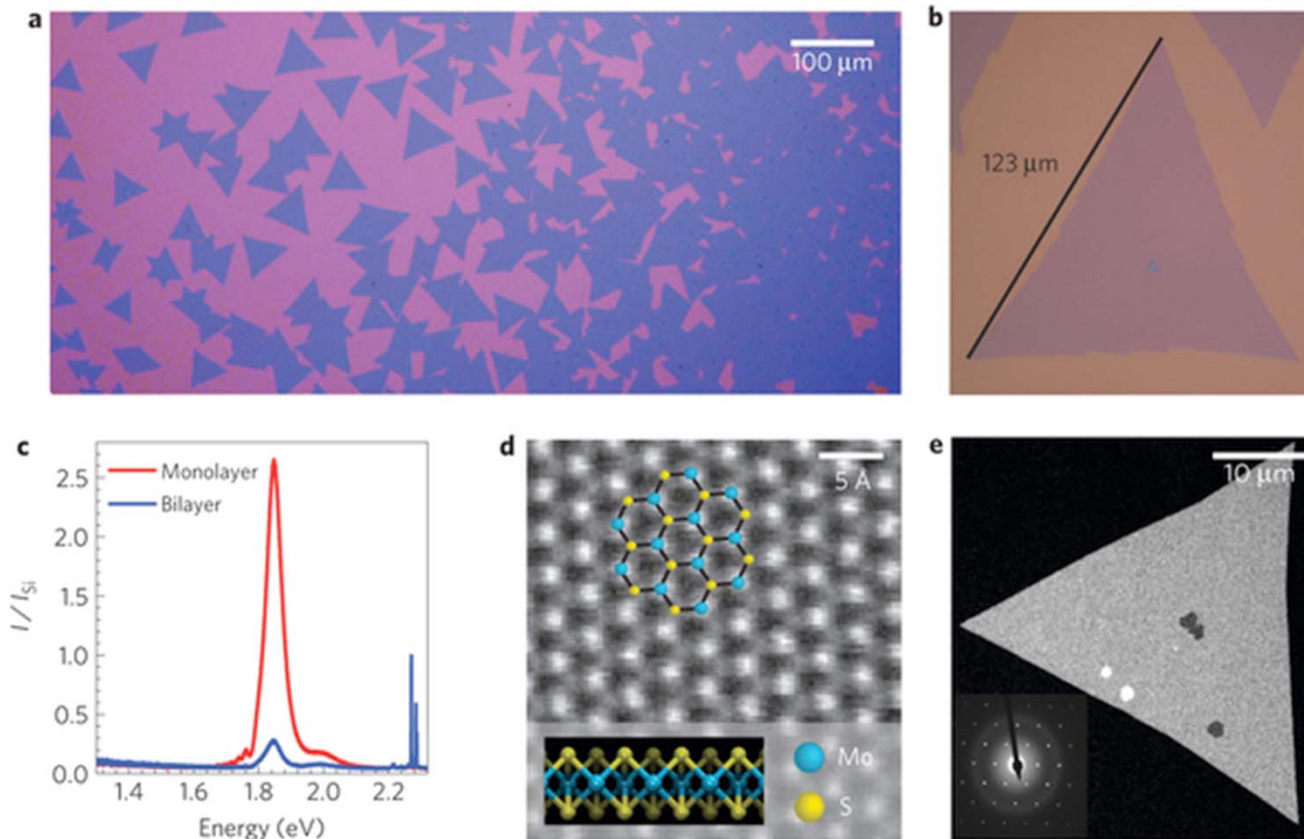
H. Wang et al, JACS 2010, 132, 3270.

CVD Growth of MoS₂ Using MoO₃ powder



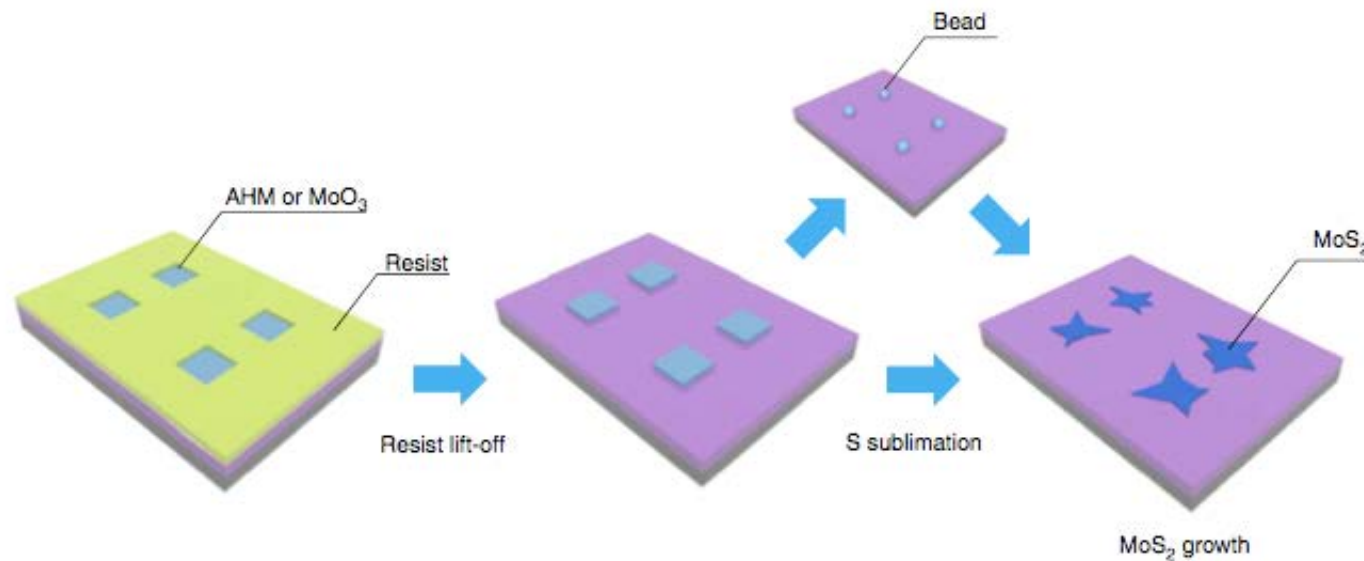
- 1) The MoO₃ powder was placed in a ceramic boat and the SiO₂/Si substrate was faced down and mounted on the top of boat.
- 2) A separate ceramic boat with sulfur powder was placed next to the MoO₃ powder.
- 3) During the synthesis of MoS₂ sheets, the reaction chamber was heated to 650 °C in a nitrogen environment.
- 4) At such a high temperature, MoO₃ powder was reduced by the sulfur vapor to form volatile suboxide MoO_{3-x}.
- 5) These suboxide compounds diffused to the substrate and further reacted with sulfur vapor to grow MoS₂ films.

MoS₂ using MoO₃ powder



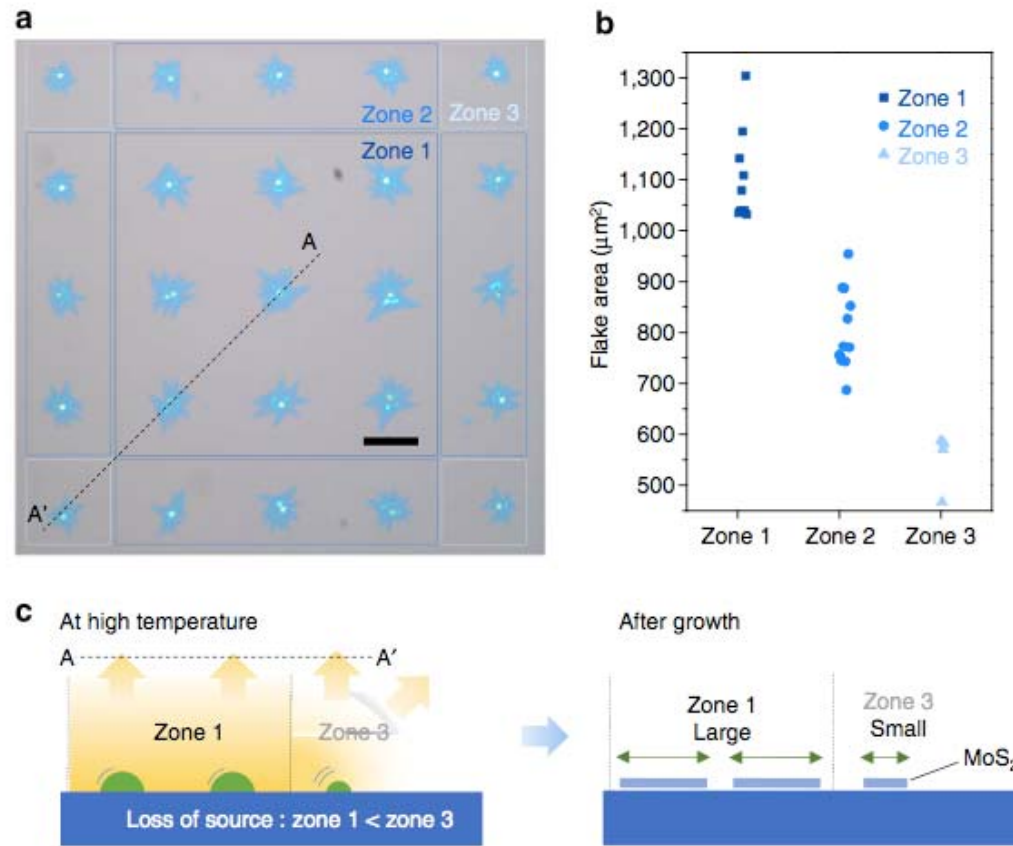
Nat. Mater. 12, p.554 (2013)

Growth of MoS₂ at Controlled Locations



- 1) Wells are locally created by conventional photolithography
- 2) Wells are filled with precursors (MoO₃ powder or Ammonium heptamolybdate ((NH₄)₆Mo₇O₂₄*4H₂O))
- 3) The photoresist is then removed
- 4) Sulfurize the substrate (Evaporation of Sulfur powder)
- 5) Growth of MoS₂ at the specified well locations.

Growth of MoS₂ at Controlled Locations

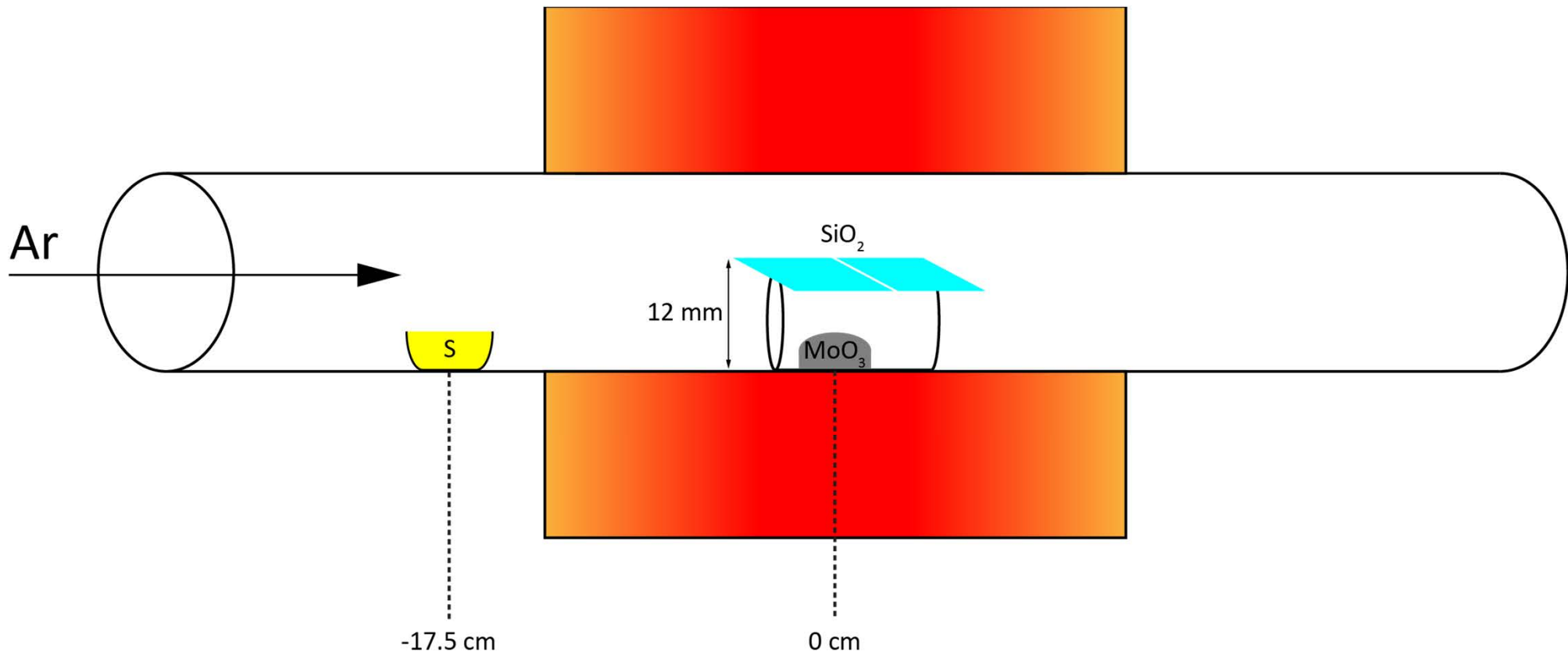


A,b) MoS₂ flake size depends on the temperature profile and the vapor pressure difference across the substrate.

: Larger flakes in the center of the substrate compared to the edge

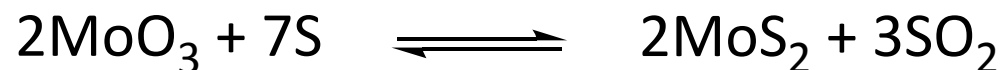
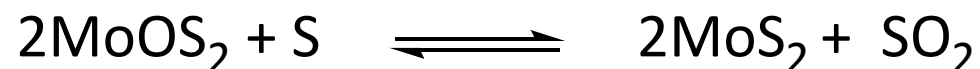
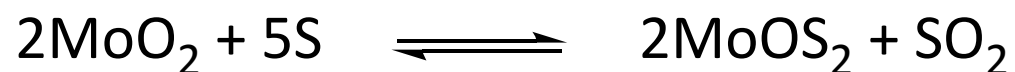
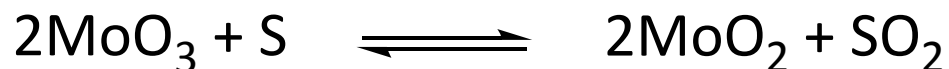
Nature Communications 6:6128 (2015)

This CVD growth is sensitive to Mo:S vapor ratio



CVD Growth of MoS₂

- Sulfur must be present at a 3.5:1 stoichiometric ratio to Mo to fully sulfurize MoO₃ to MoS₂
- Loading S at a ratio >> 3.5:1 is necessary to ensure the reaction goes to completion because the intermediates are stable

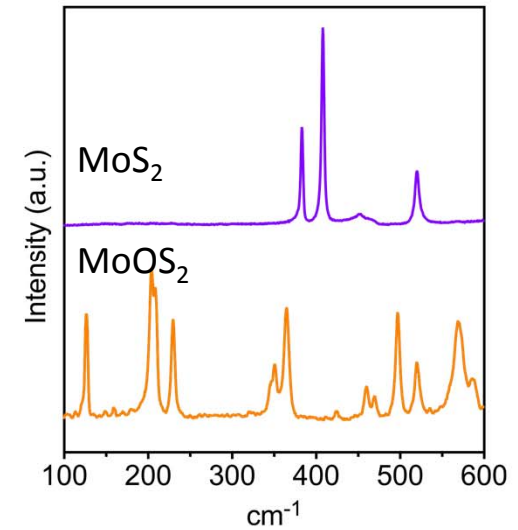
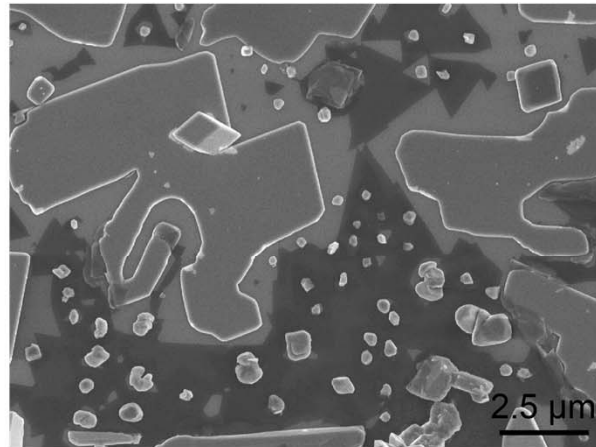
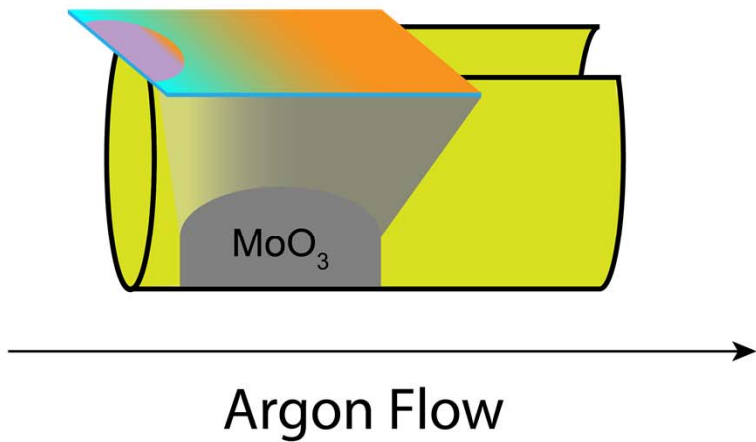


T. Weber, *et al.*, *J. Phys. Chem.* 100, 1996.

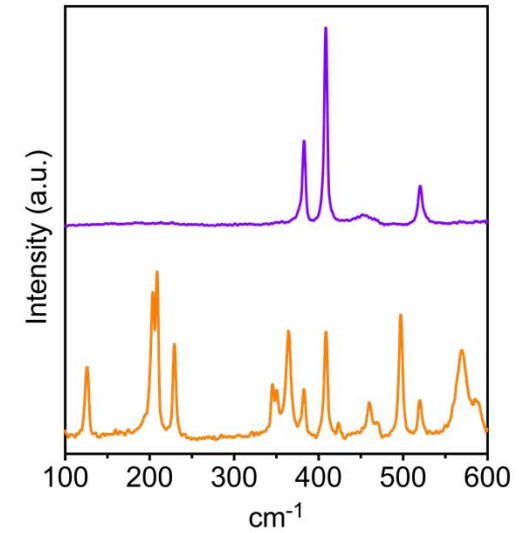
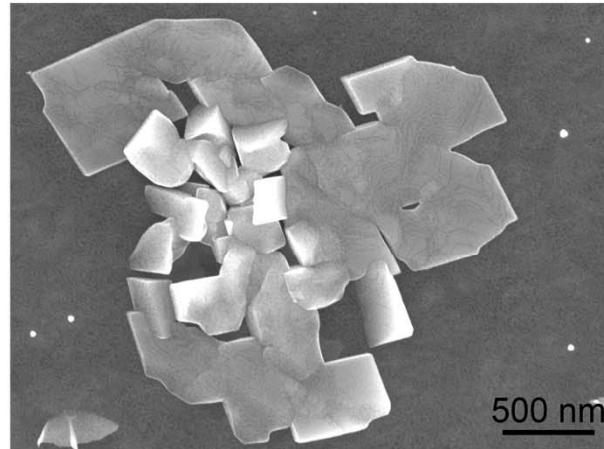
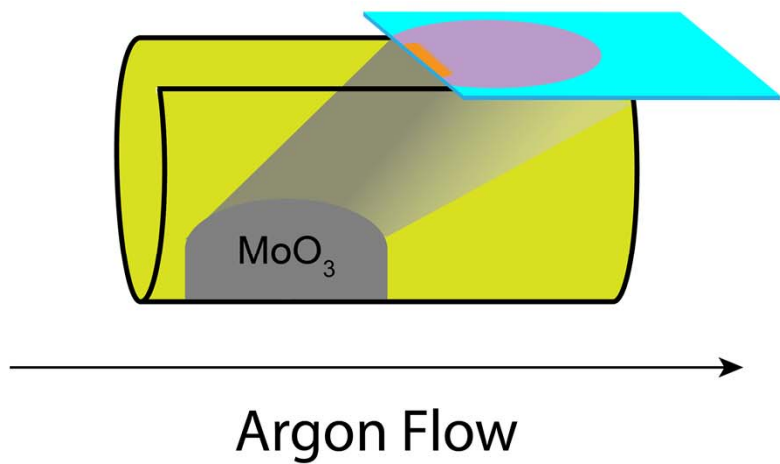
X. Li, *et al.* *S. Chem.-A Eur. J.* 9, 2003.

S. Najmaei, *et al.* *Nat. Mater.* 12, 2013.

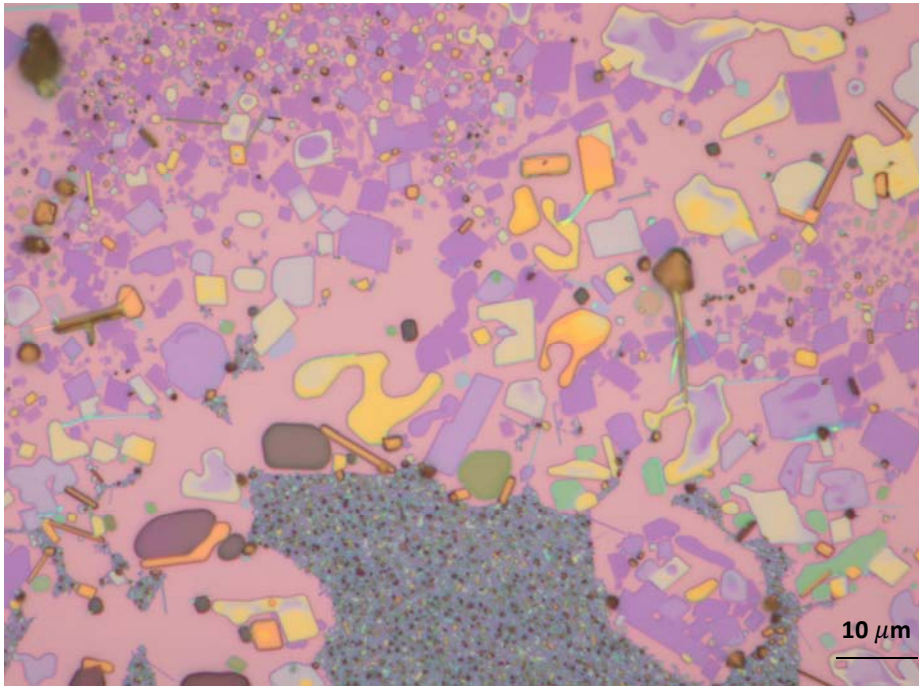
CVD Growth of MoS₂: Locally Increased S:Mo Ratio



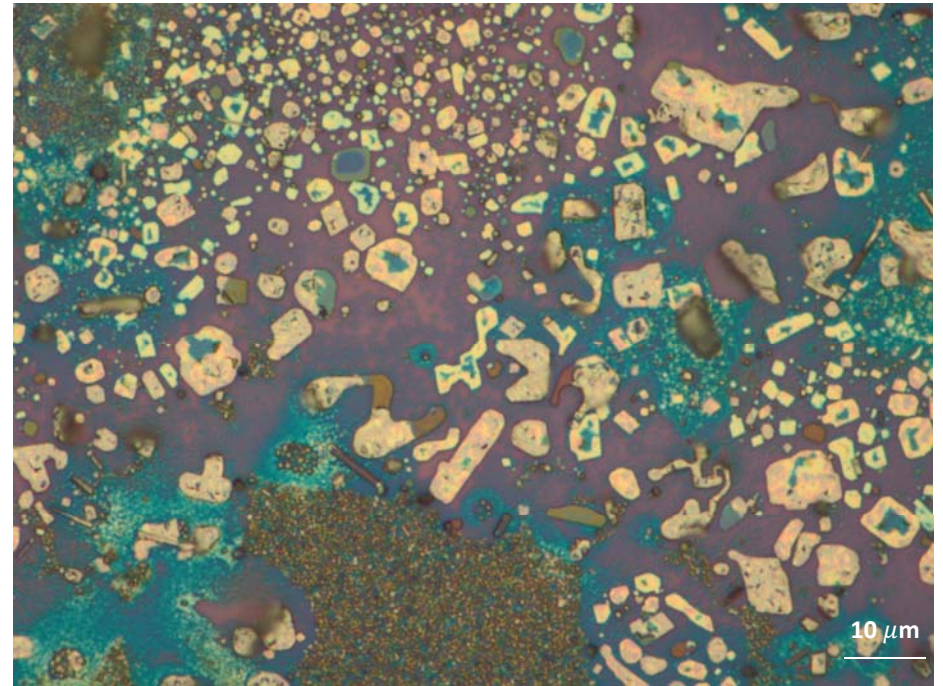
CVD Growth of MoS₂: Locally Decreased S:Mo Ratio



Sulfurization of MoOS₂



MoOS₂ Crystals

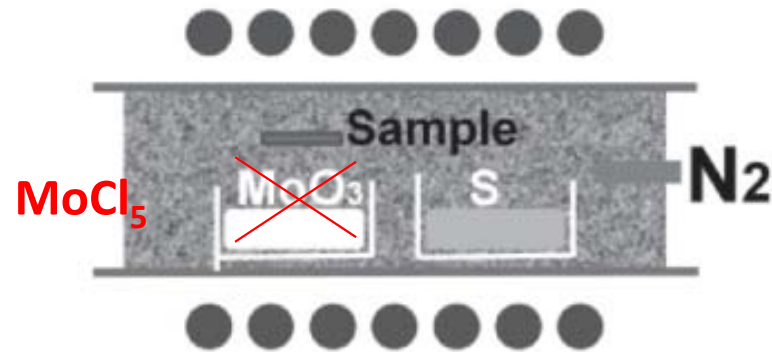


MoS₂ Crystals After Sulfurization

Sulfurization of MoOS₂

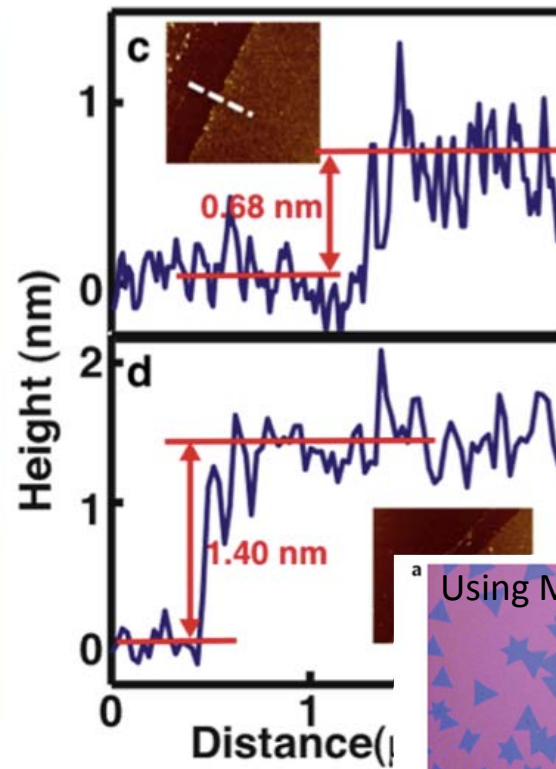
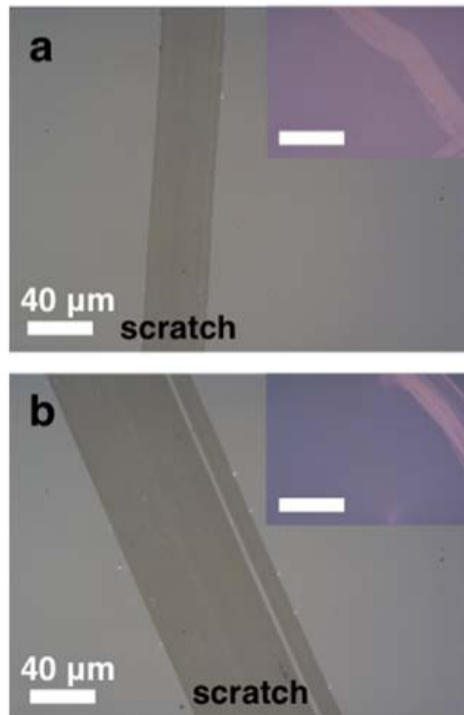


CVD Growth of MoS₂ Using MoCl₅ powder



- MoCl₅ and S powders were heated to 800 C .
- Various substrates were successful in growing MoS₂
 - SiO₂, Sapphire (Al₂O₃), Graphite
- Large-area, continuous MoS₂ film
- The # of layers of MoS₂ could be controlled by tuning the MoCl₅ amount, which controls the partial pressure of dissociated Mo vapor.

CVD Growth of MoS₂ Using MoCl₅ powder



A: single-layer MoS₂
B: bi-layer MoS₂

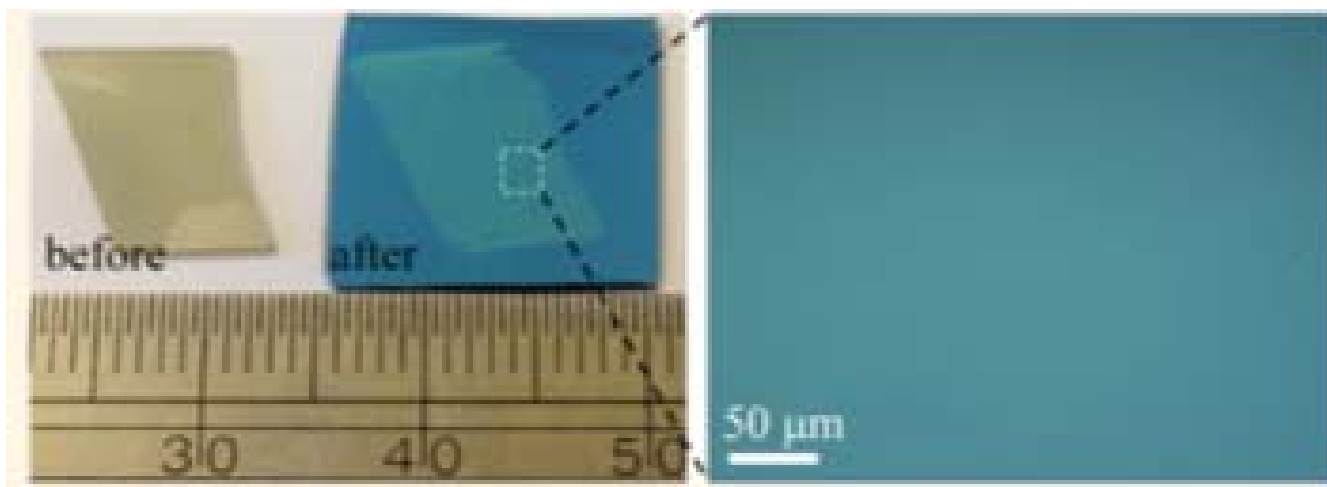
Main panel: Sapphire substrate
Inset: SiO₂/Si substrate

Continuous Films. Made a scratch to check the film thickness.



Scientific Report, 3:1866 (2013)

Transfer of Cm-scale MoS₂ onto Arbitrary Substrates



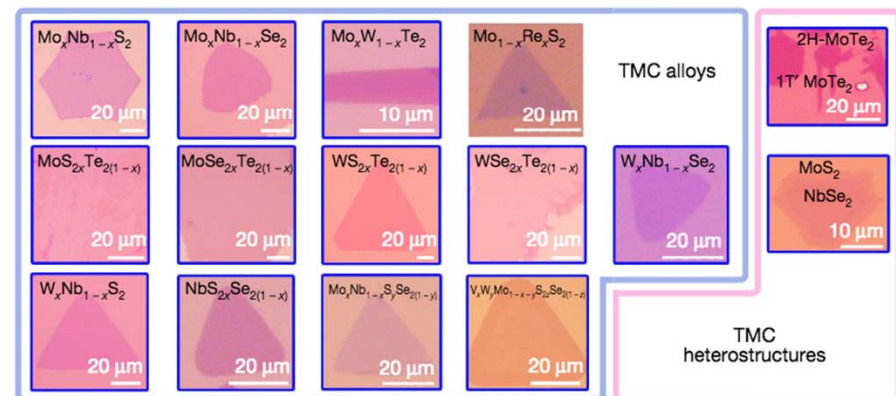
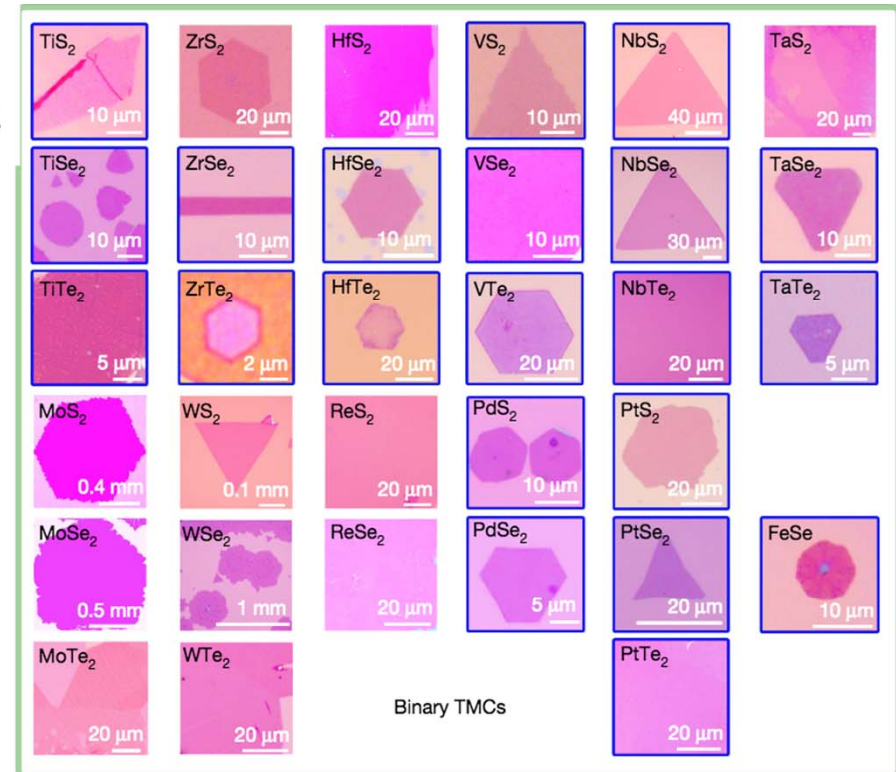
Large-area, single-layer MoS₂ film being transferred from growth substrates to other substrates
- Necessary if growth substrates are not compatible with device substrates

A library of atomically thin metal chalcogenides

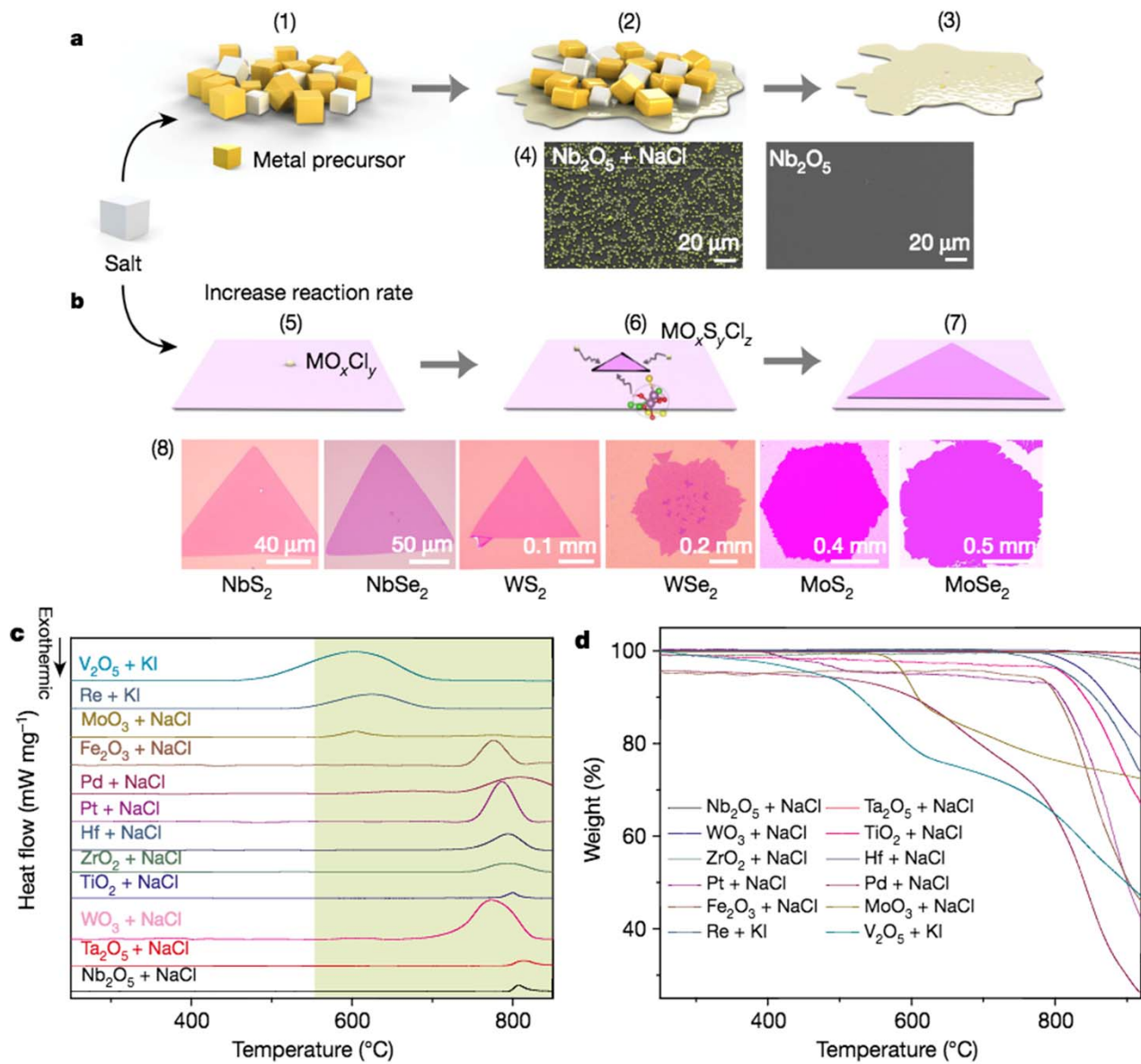
Jiadong Zhou^{1,15}, Junhao Lin^{2,15*}, Xiangwei Huang³, Yao Zhou⁴, Yu Chen⁵, Juan Xia⁵, Hong Wang¹, Yu Xie⁶, Huimei Yu⁷, Jincheng Lei⁶, Di Wu^{8,9}, Fucui Liu¹, Qundong Fu¹, Qingsheng Zeng¹, Chuang-Han Hsu^{8,9}, Changli Yang^{3,10}, Li Lu^{3,10}, Ting Yu⁵, Zexiang Shen⁵, Hsin Lin^{8,9,11}, Boris I. Yakobson⁶, Qian Liu⁴, Kazu Suenaga², Guangtong Liu^{3*} & Zheng Liu^{1,12,13,14*}

a

	IIIB	IVB	VB	VIB	VIIIB	VIII		IB	VA	VIA	VIIA
Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	P	S	Cl
21	22	23	24	25	26	27	28	29	15	16	17
Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	As	Se	Br
39	40	41	42	43	44	45	46	47	33	34	35
La	Hf	Ta	W	Re	Os	Ir	Pt	Au	Sb	Te	I
57	72	73	74	75	76	77	78	79	51	52	53



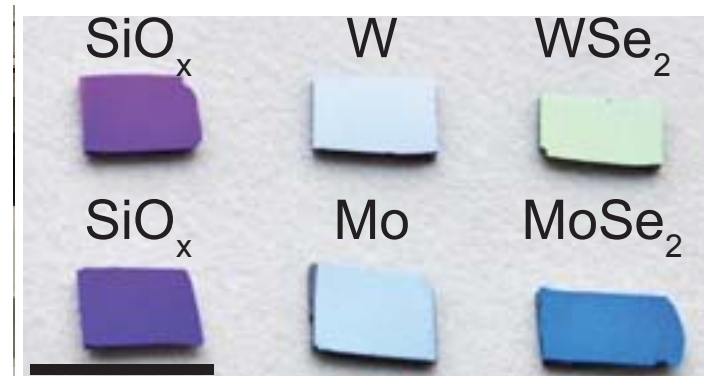
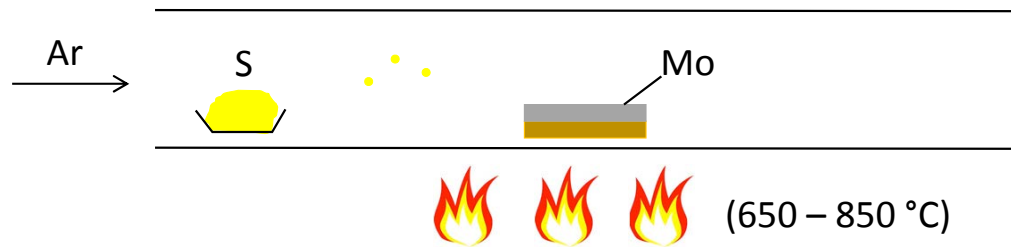
Nature 556, 355 (2018)



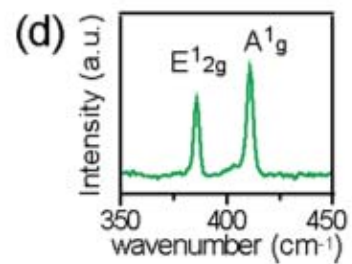
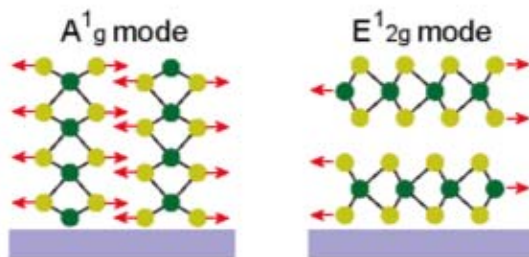
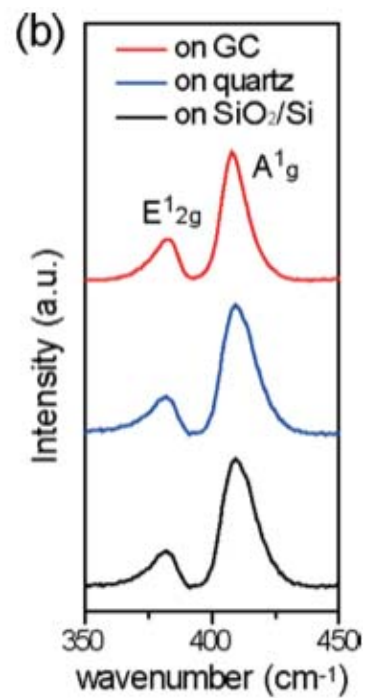
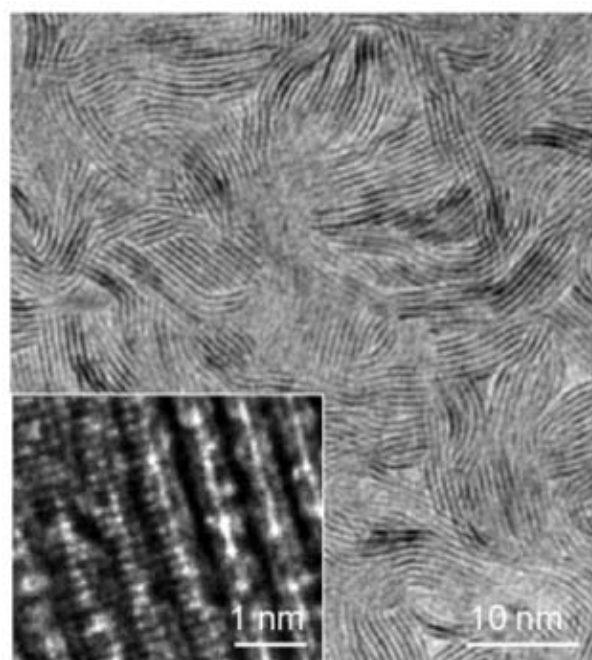
Synthesis of Vertically-Aligned MoS₂ Film

Growth:

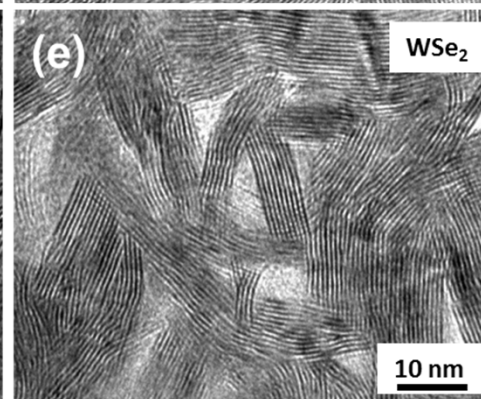
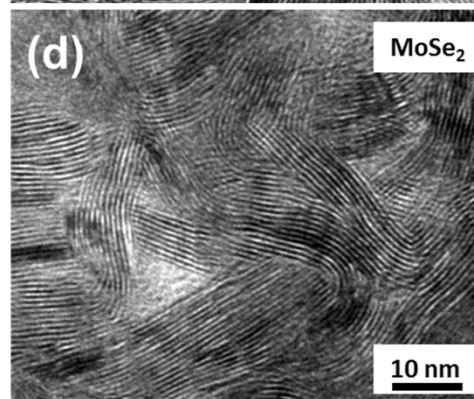
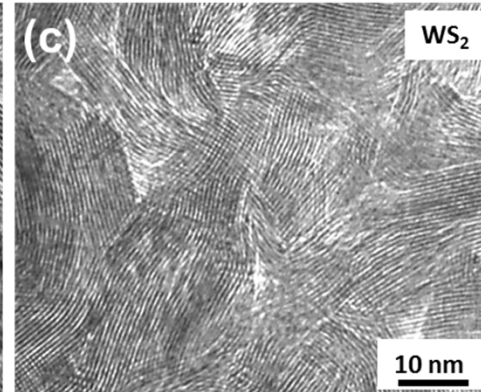
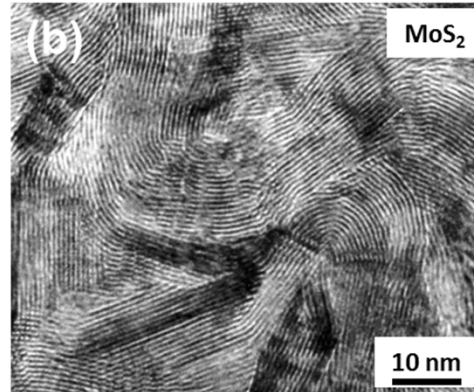
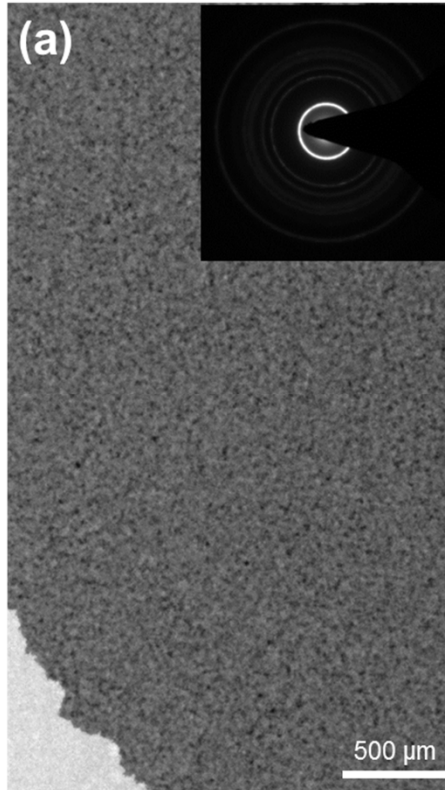
Sulfurization of Mo/SiO₂ & W/SiO₂ substrates



Synthesis of Vertically-Aligned MoS₂ Film

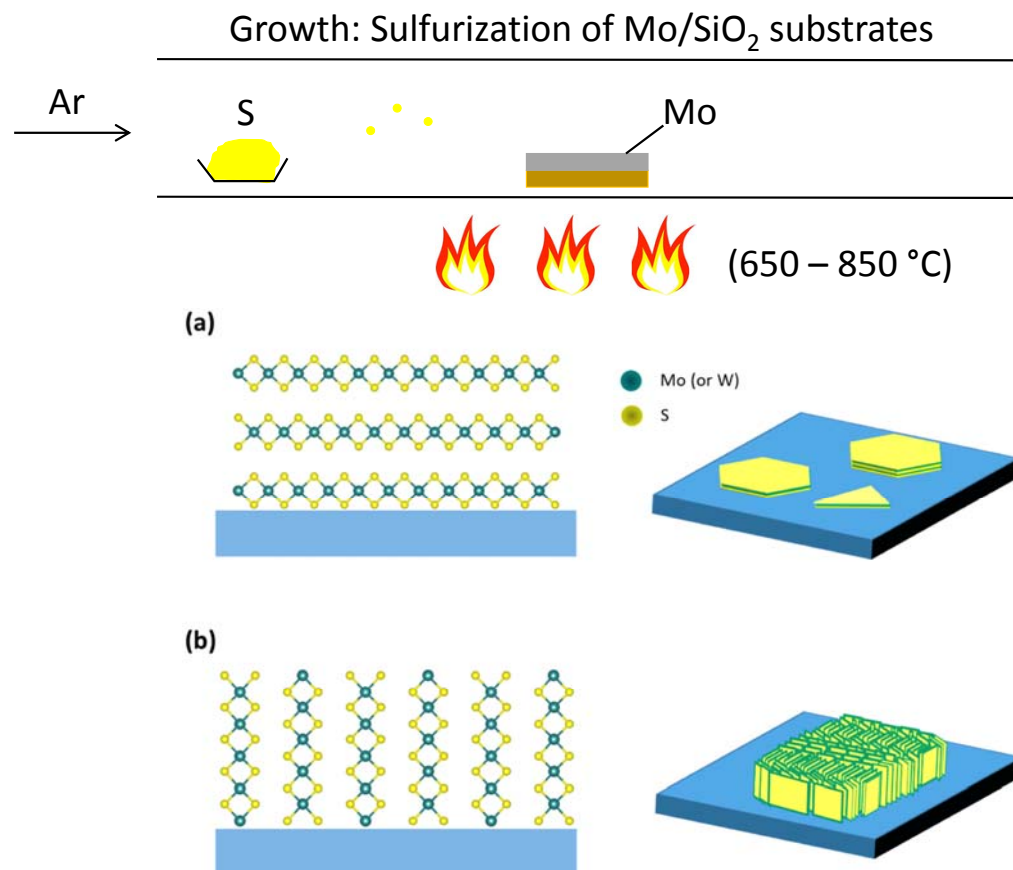


Large-Area, Densely-Packed Films



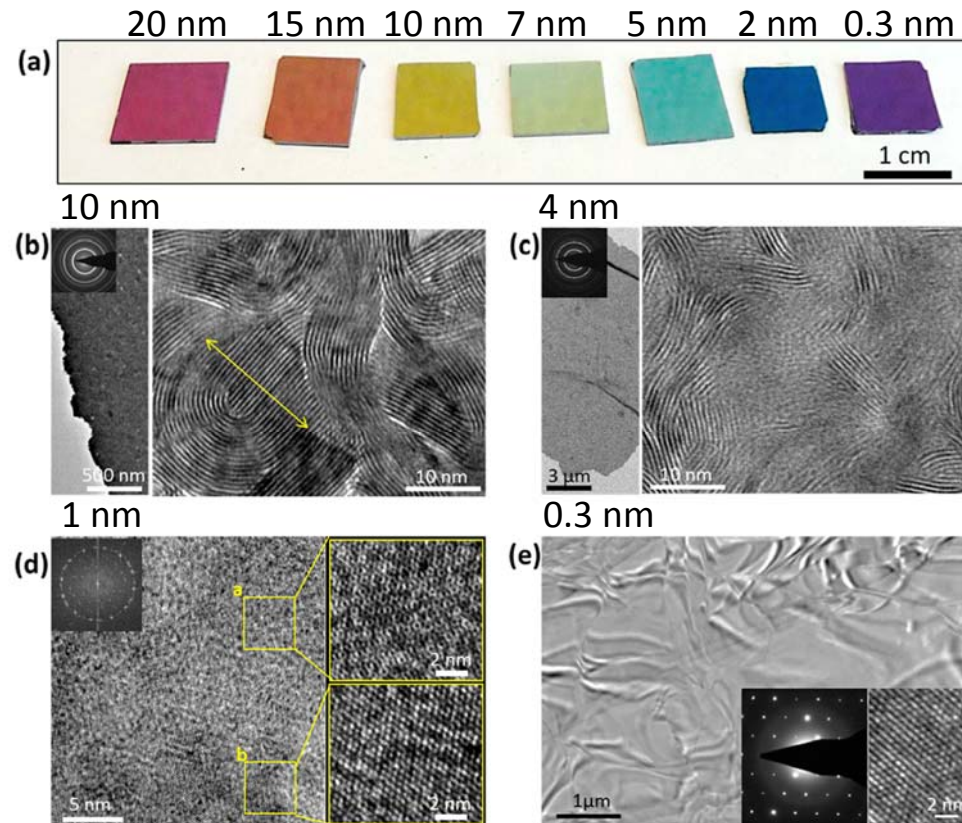
Vertical to Horizontal Growth of MoS₂

Why do we grow MoS₂ vertically even though growth conditions are similar?

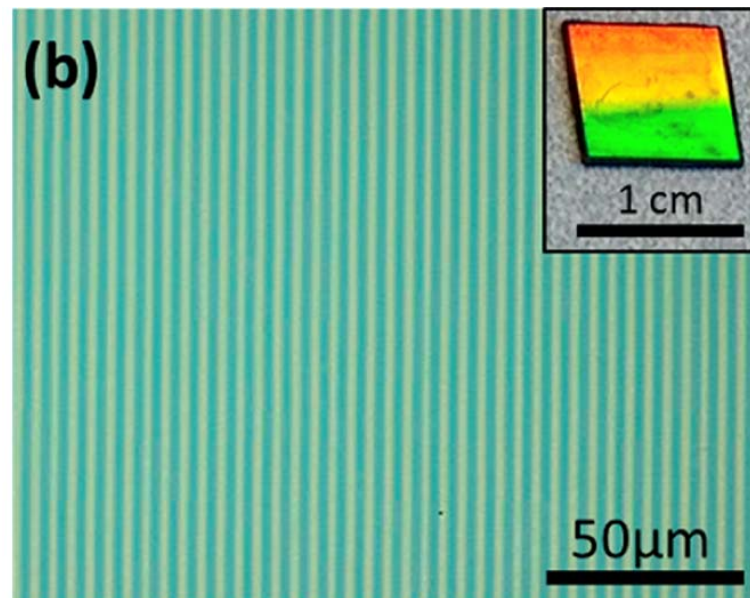
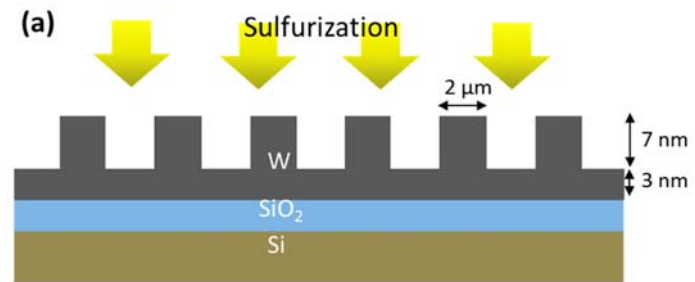


Nano Lett. 14, 6842 (2014)

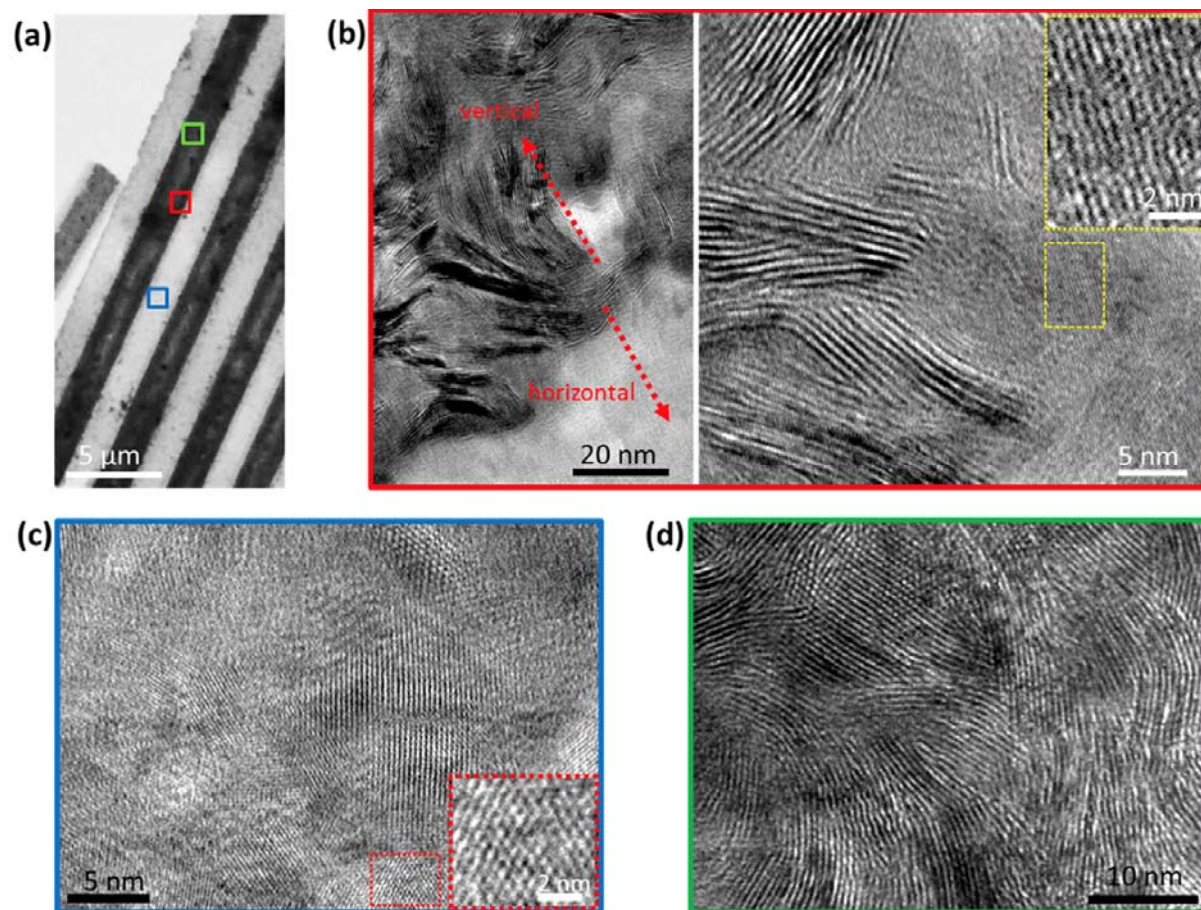
Mo Film Thickness-Dependent MoS₂ Growth



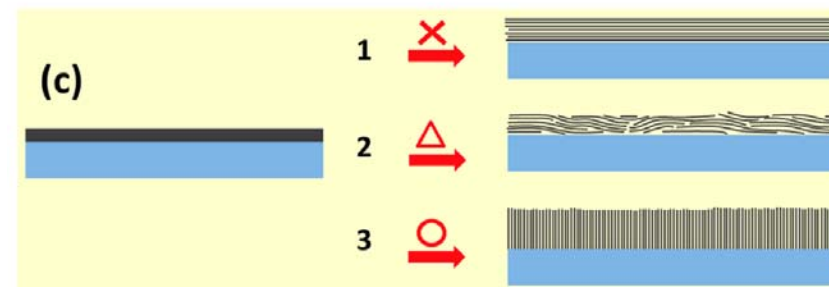
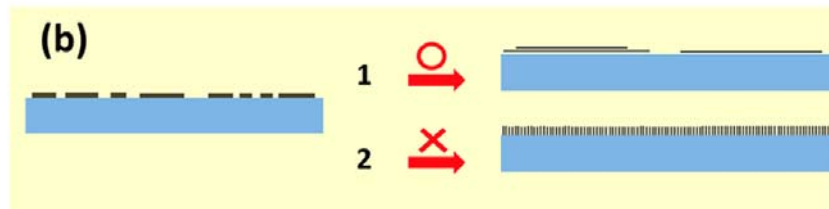
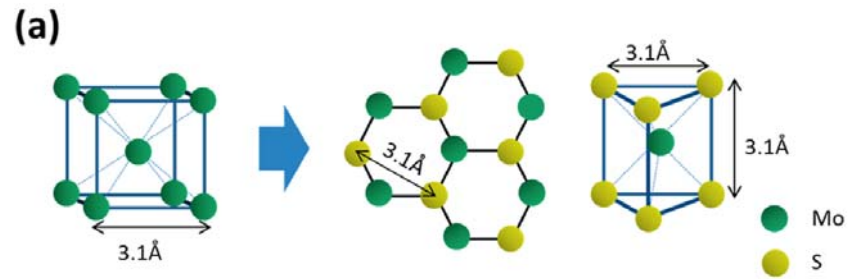
W Film Thickness-Dependent WS_2 Growth



Vertical and Horizontal WS₂ Films



Volume Expansion and Strain Effects



Overview

- Why Nanoscale Materials
 - Emergent properties (band engineering, surface properties)
 - Examples (quantum dots, carbon nanotubes, mechanical properties)
- Synthesis of Nanowires
 - Various growth methods
 - Vapor-liquid-solid growth
 - Doping / surface passivation
- Synthesis of 2D Materials
 - Chemical vapor deposition
 - Precursors / additives

Overview

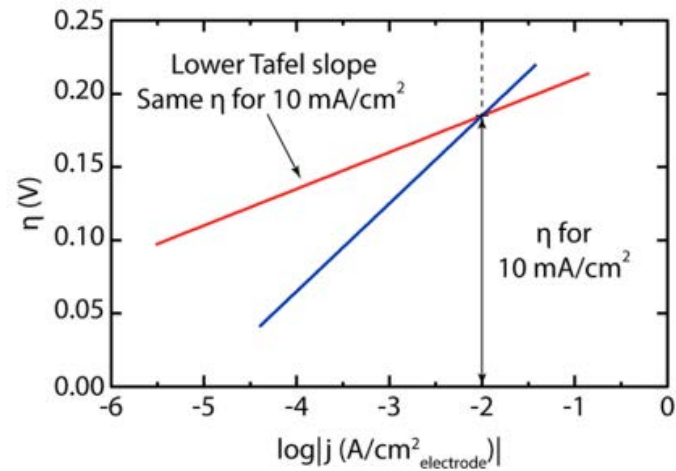
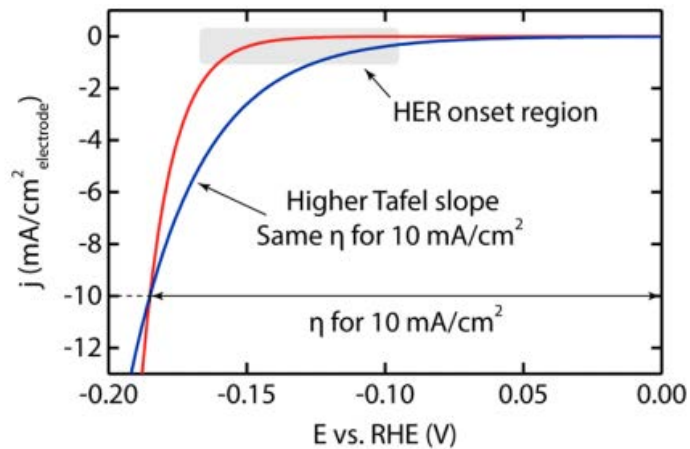
- Case Study of Nanowires: Si Nanowires
 - Thermal transport modulation
 - Si nanowire batteries
- Case study of topological nanomaterials
 - Bi_2Se_3 topological insulator nanoribbons
 - SnTe Topological crystalline insulator nanowires
- Case study of 2D materials for energy
 - MoS_2 for hydrogen evolution reaction (HER)
 - Phase transition via intercalation and consequences for HER

Hydrogen Evolution Reaction (HER)

Water Splitting: $\text{H}_2\text{O} \rightarrow \text{H}_2 + 1/2\text{O}_2$

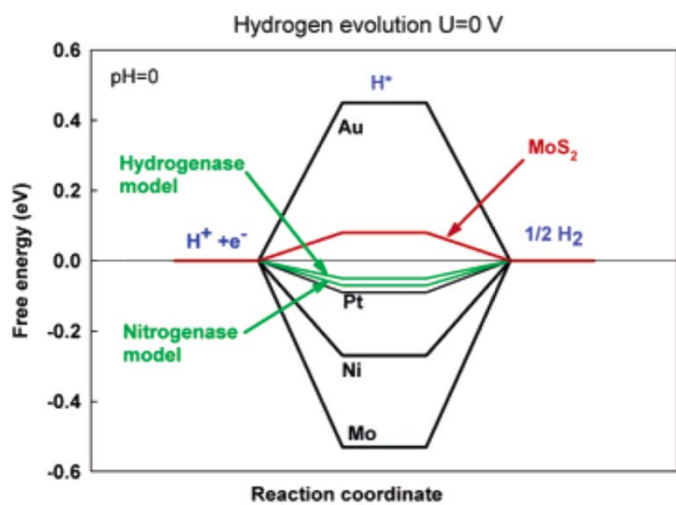
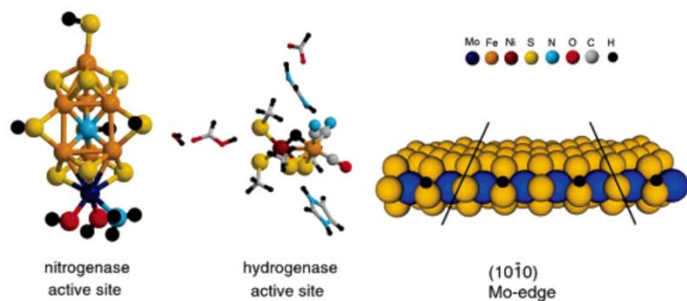
Hydrogen Evolution Reaction (HER): $2\text{H}^+ + 2\text{e}^- \rightarrow \text{H}_2$

Oxygen Evolution Reaction (OER): $\text{H}_2\text{O} \rightarrow 1/2\text{O}_2 + 2\text{H}^+ + 2\text{e}^-$

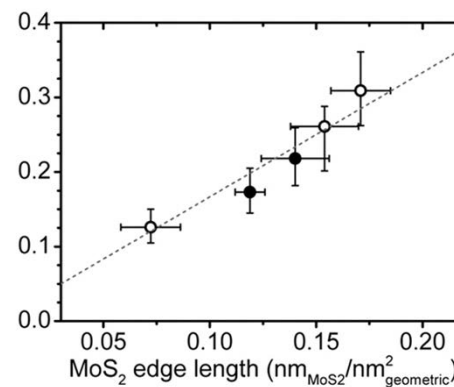
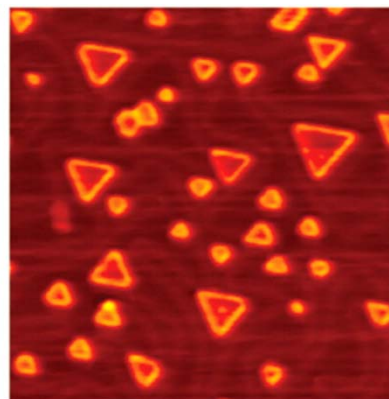


Low overpotential, low Tafel slope

MoS₂ as a Promising HER Catalyst

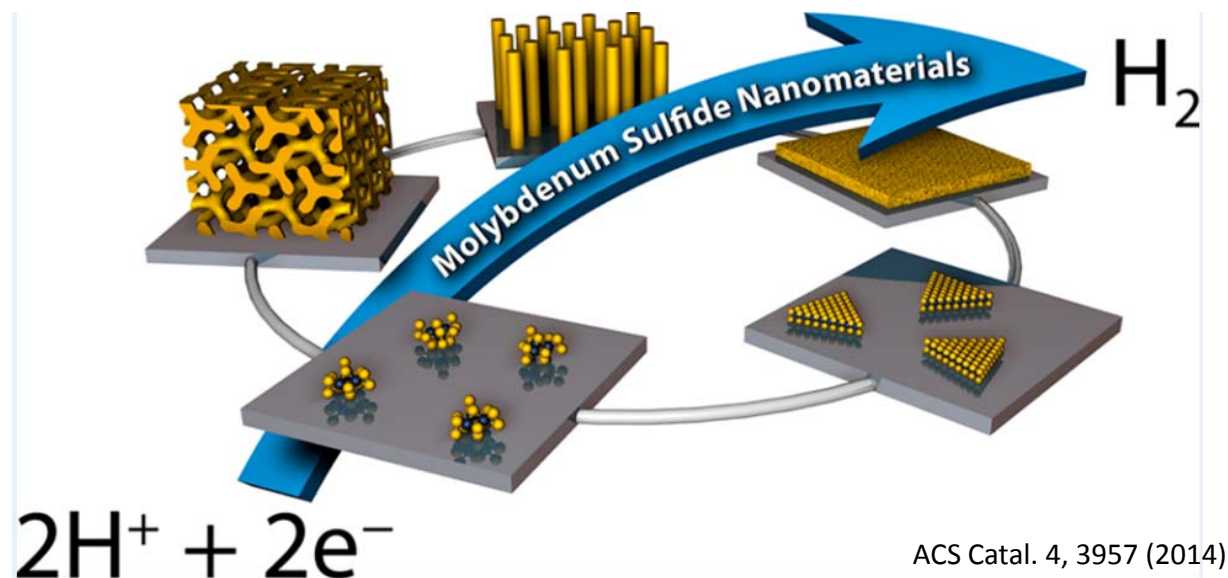


JACS 127, p.5308 (2005)



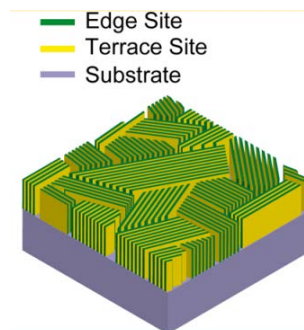
Science 317, 100 (2007)

Catalyzing the HER with MoS₂ Nanomaterials

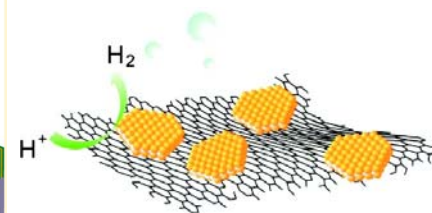


Progress in MoS₂ as HER catalyst

1. Increase S edge sites
2. Better transfer to current collector
3. Improve electrical properties
4. ΔG_{H} tuning to lower energy barrier



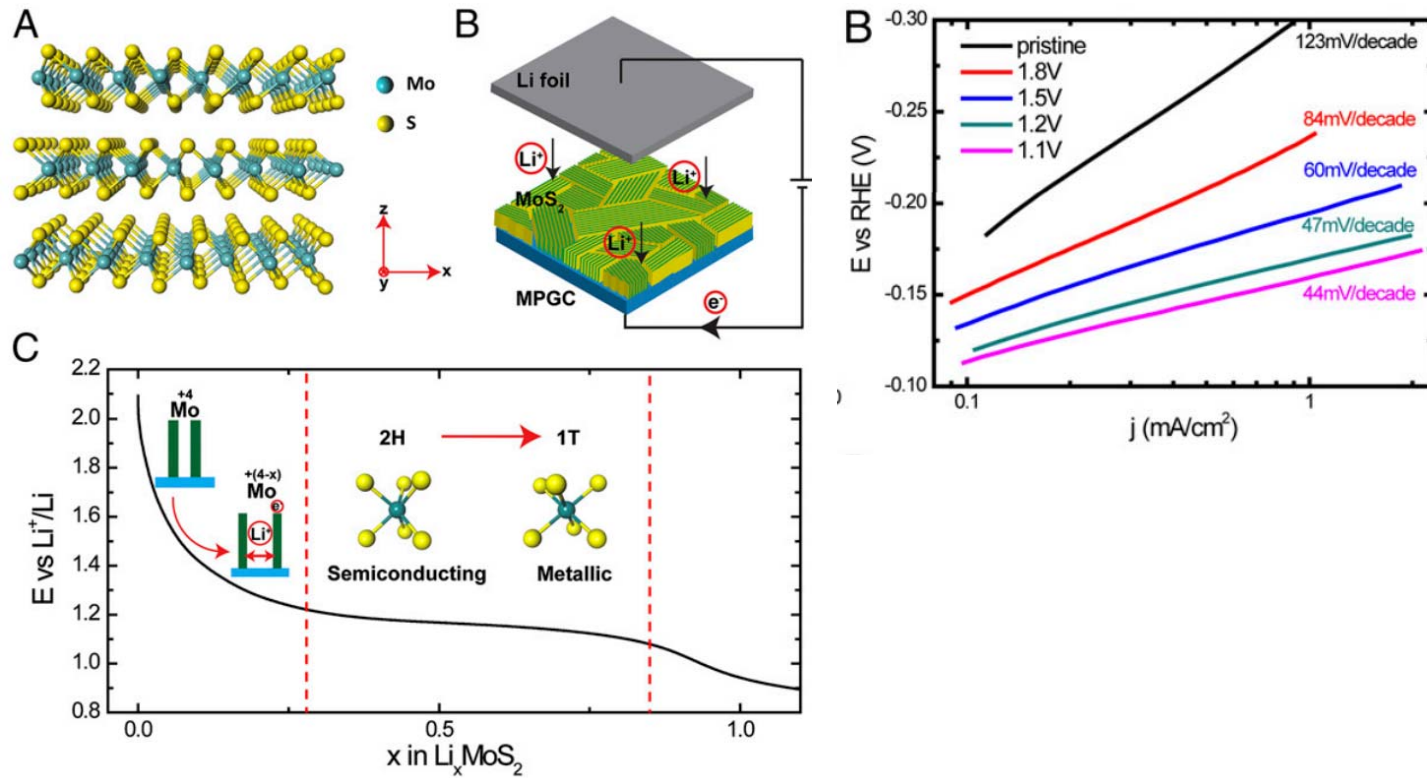
Nano Lett. 13, 1341 (2013)



JACS 133, 7296 (2011)

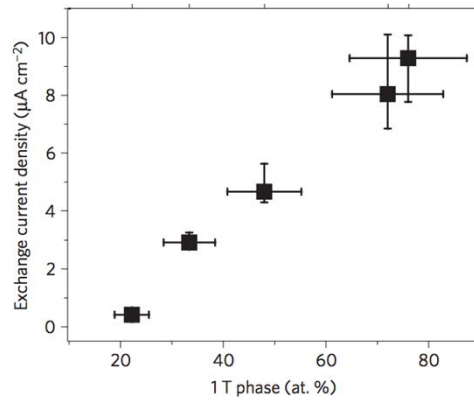
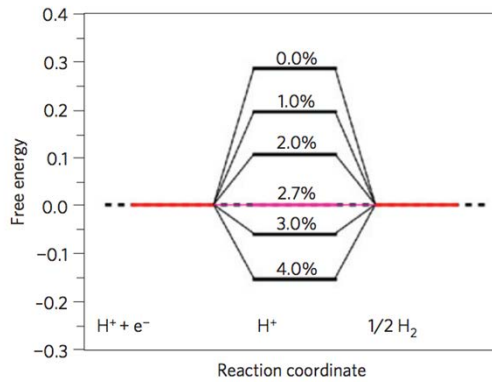
Improve Electronic Property

Phase transition from semiconducting 2H \rightarrow metallic 1T : Lower Tafel slope



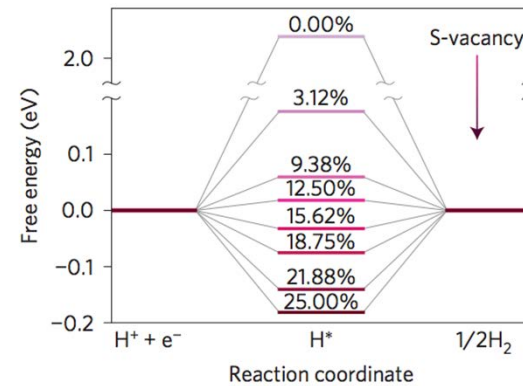
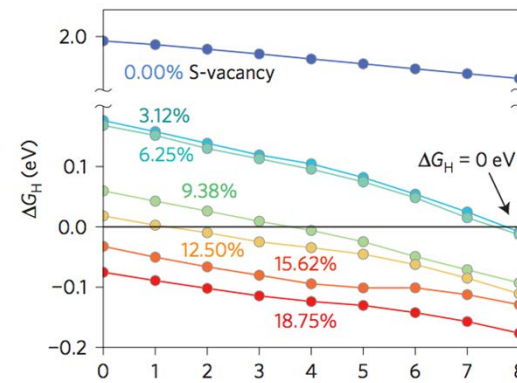
Tuning ΔG_H to improve HER

WS₂: Strain engineering by 1T'
2H → 1T' by Li⁺ exfoliation



Nat. Mater. 12, p.850 (2013)

MoS₂: Strain engineering by S vacancies
Basal plane activation



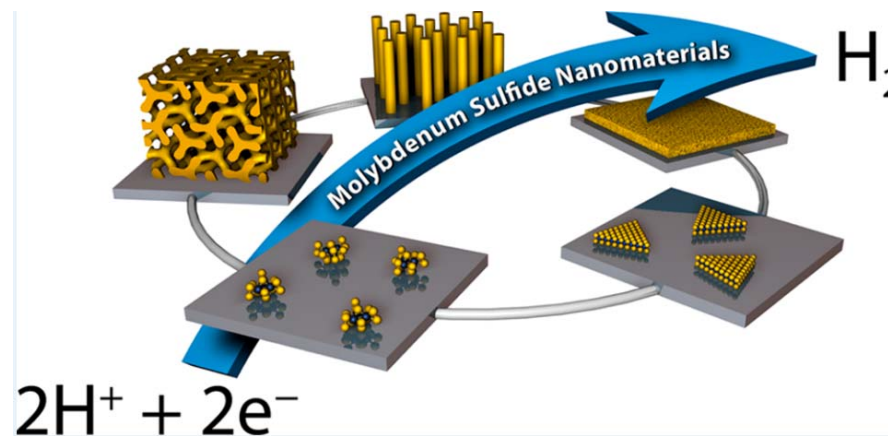
Nat. Mater. 15, p.48 (2016)

Interconnected HER Parameters

Progress in MoS₂ as HER catalyst

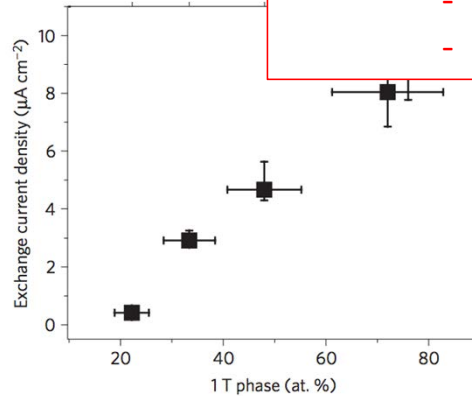
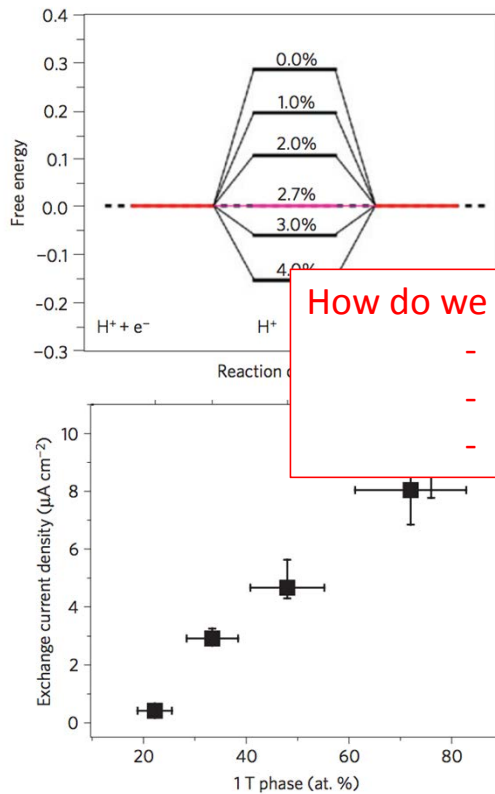
1. Increase S edge sites
2. Better transfer to current collector
3. Improve electrical properties $2H \rightarrow 1T'$, but also changes ΔG_H
4. ΔG_H tuning to lower energy barrier Effects of S vacancies on conductivity?

HER parameters: ΔG_H , σ , $\Phi_{\text{interface}}$. What's most important?



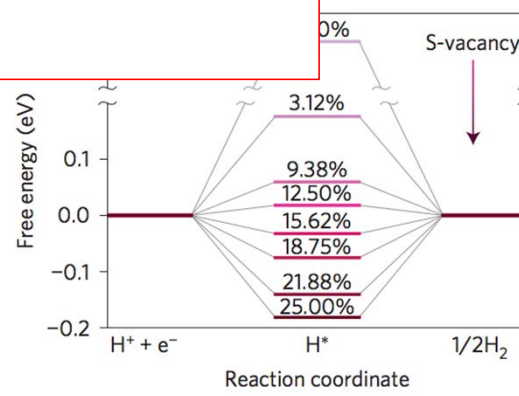
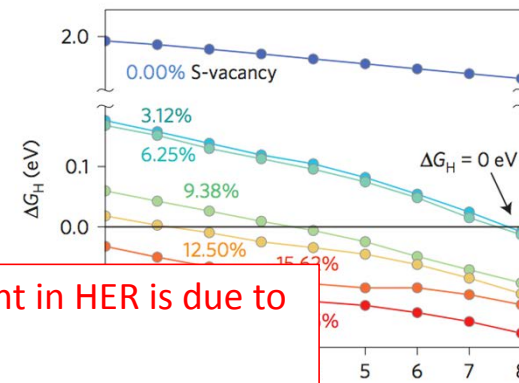
Tuning ΔG_H to improve HER

WS₂: Strain engineering by 1T'
2H → 1T' by Li⁺ exfoliation



Nat. Mater. 12, p.850 (2013)

MoS₂: Strain engineering by S vacancies
Basal plane activation

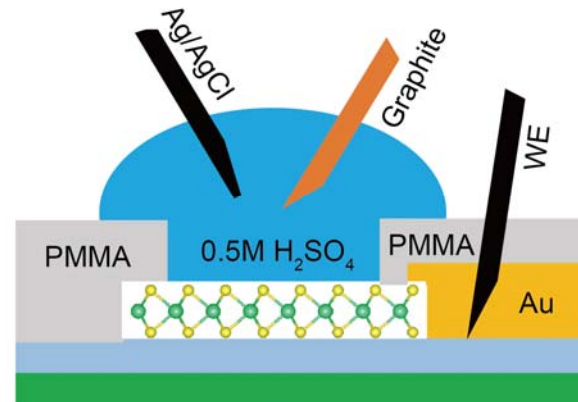
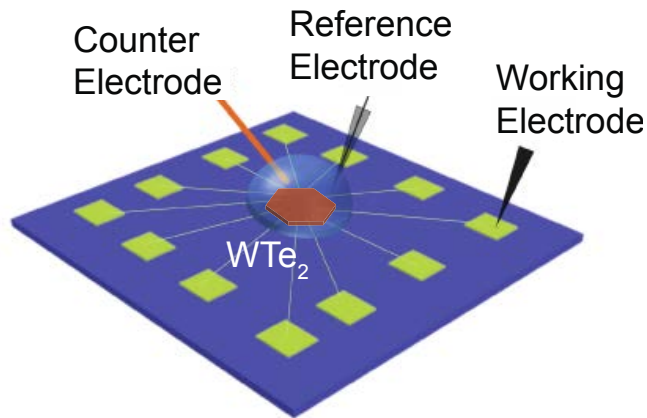


Nat. Mater. 15, p.48 (2016)

How do we tell if improvement in HER is due to

- ΔG_H tuning
- Improving σ
- Lowering Φ_{SC}

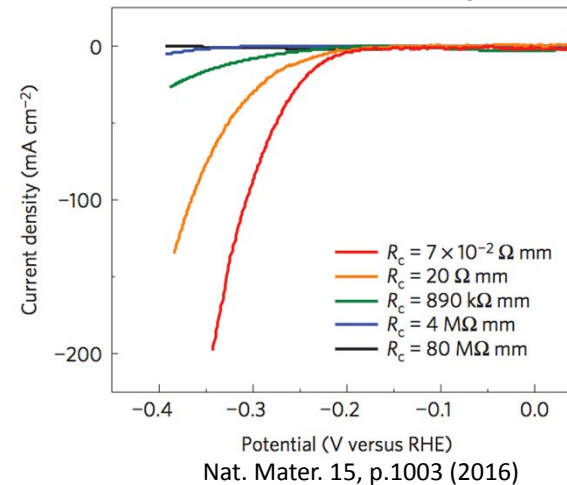
Nanodevices as Micro-reactors for HER



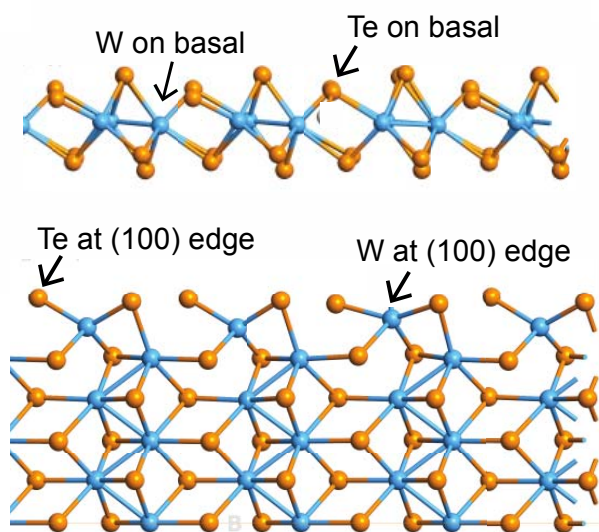
We accurately control and measure

- Types and densities of active sites (ΔG_H)
- Electron transport within catalyst (σ)
- Electron transfer at interface (Φ_{SC})

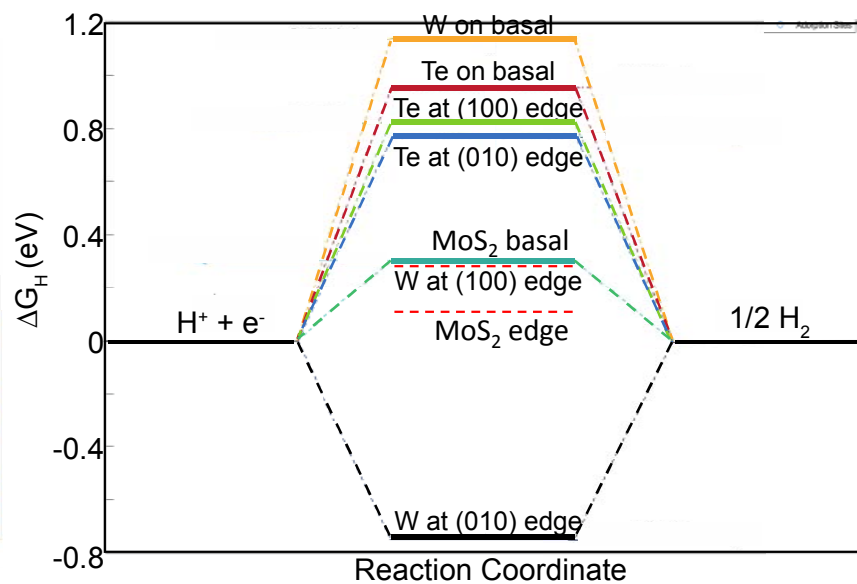
Basal plane MoS_2 with R_c tuning



MoS₂ and WTe₂: Contrasting Model Systems

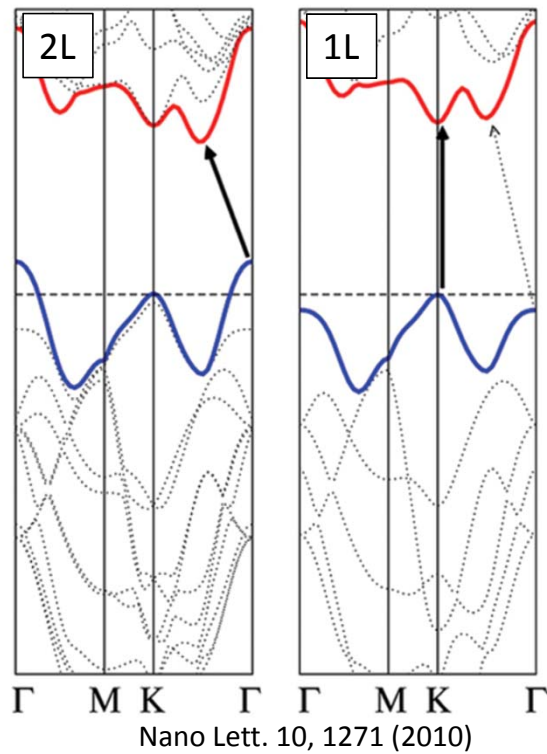


Moyses Araujo from Uppsala University



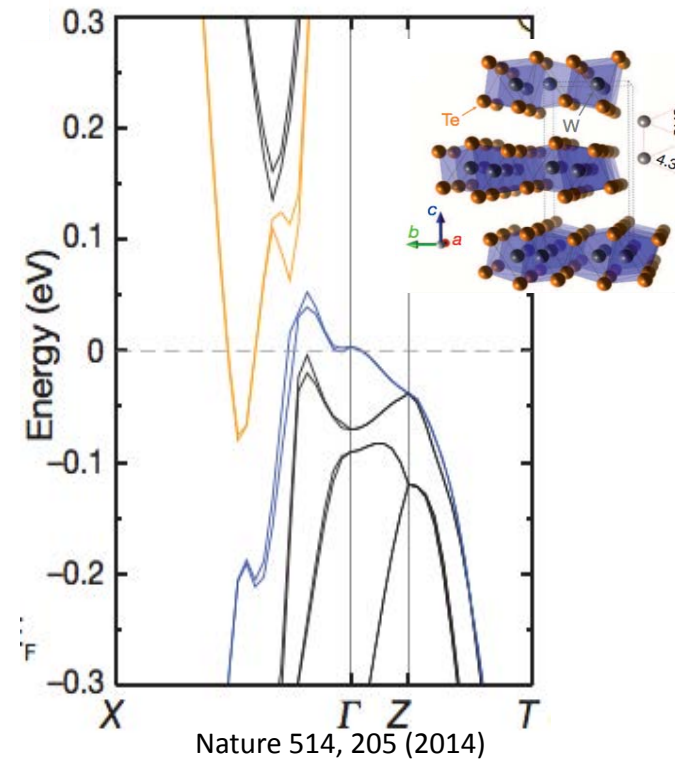
MoS₂ and WTe₂: Contrasting Model Systems

Semiconducting MoS₂ (2H)



Mobility (μ) \sim 100 cm²/Vs

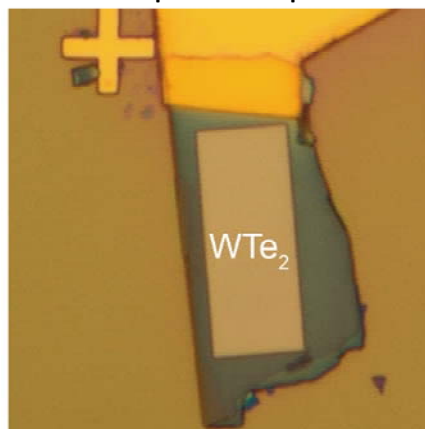
Semimetallic WTe₂ (T_d)



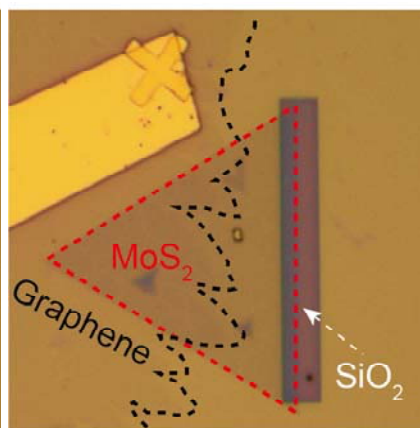
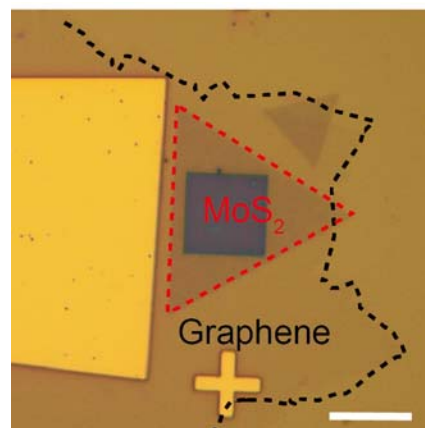
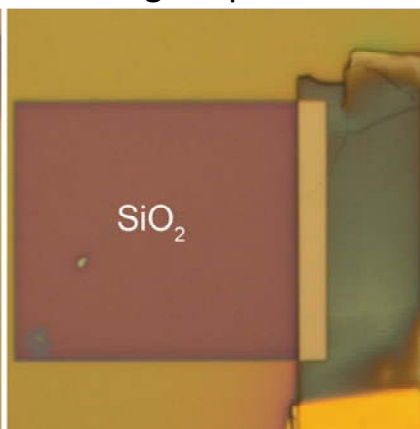
Mobility (μ) \sim 10,000 cm²/Vs

Nanodevice HER Micr-reactor

Basal plane exposed

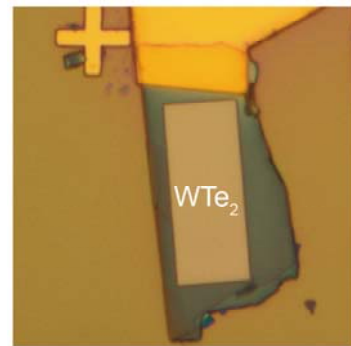
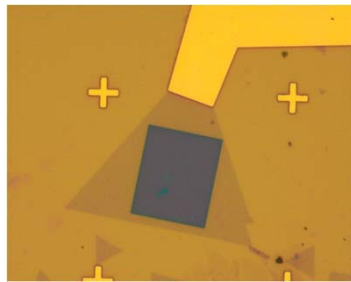


Edge exposed

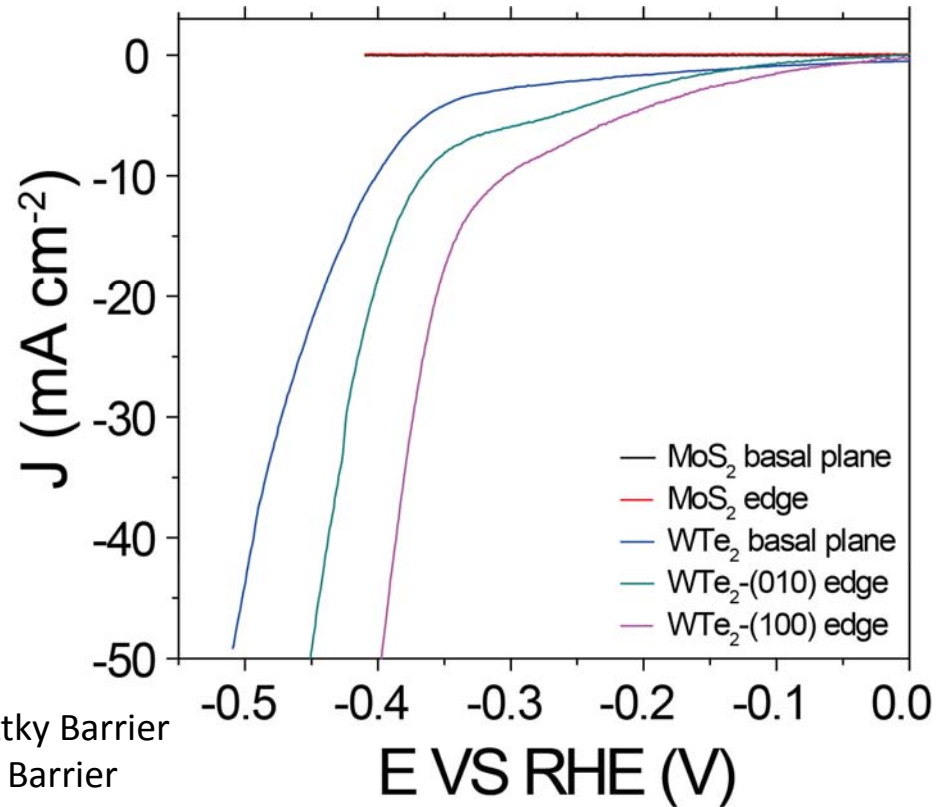


Modulating Schottky Barrier (Φ_{sc})

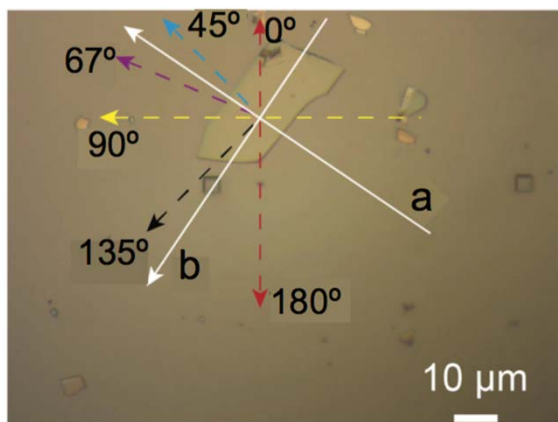
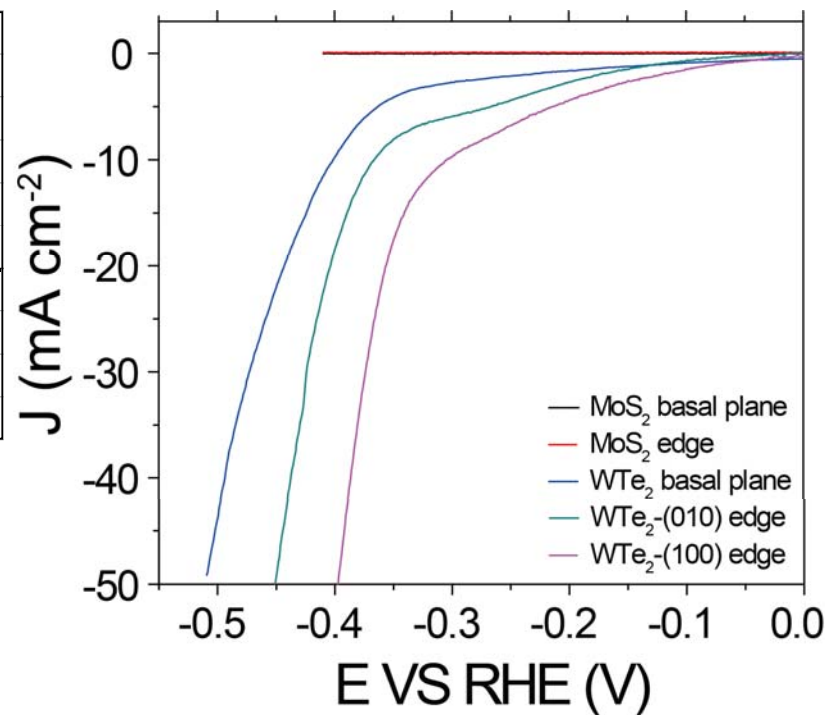
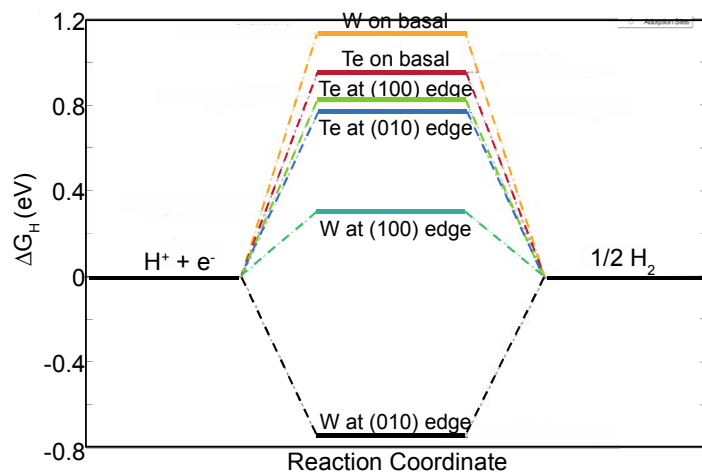
Using Au as electrodes



MoS₂/Au : Large Schottky Barrier
WTe₂/Au: No Schottky Barrier

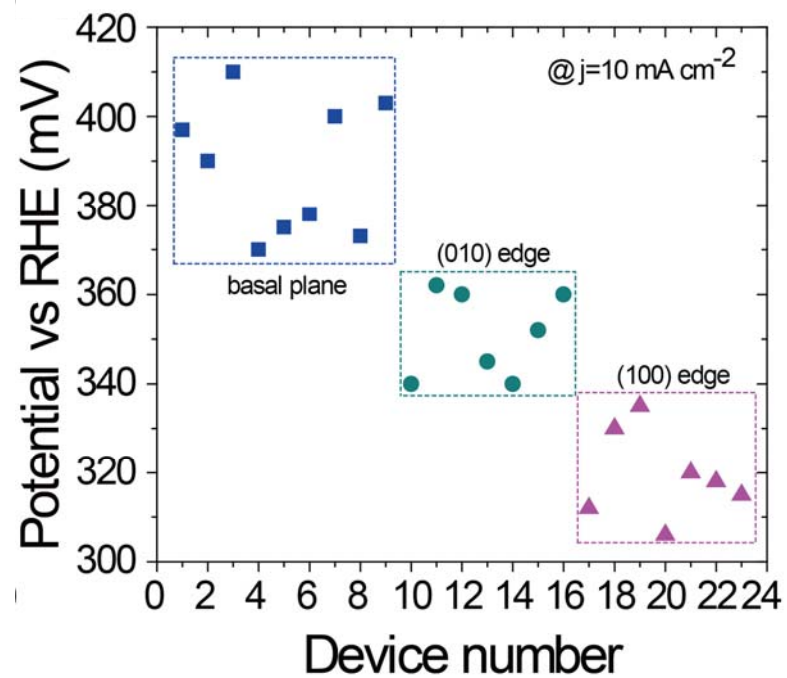
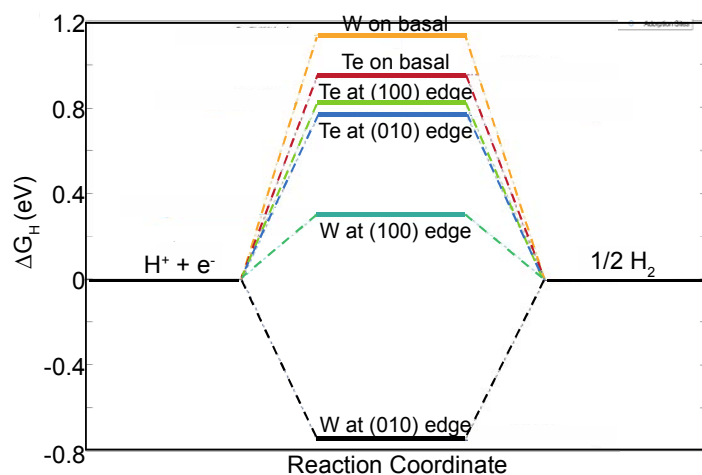


ΔG_H effect in WTe_2



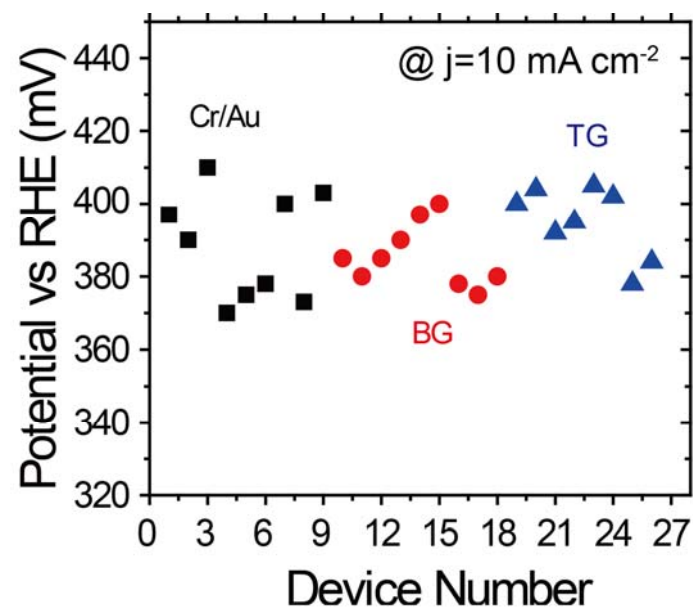
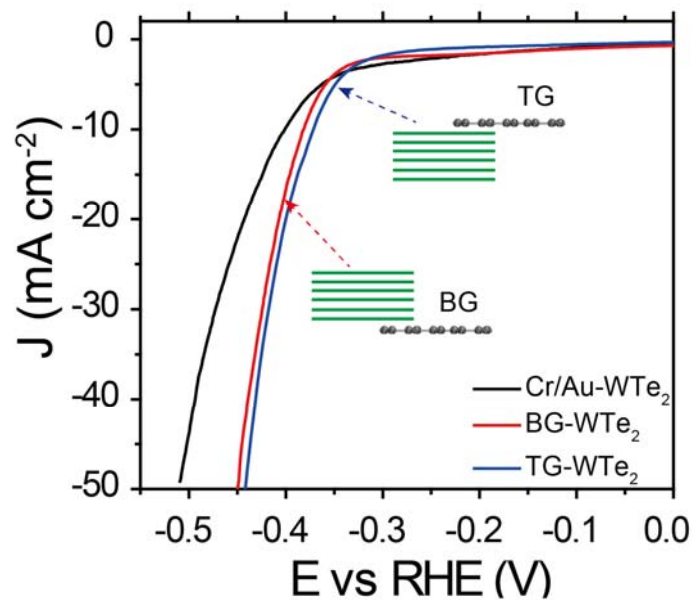
With F. Xia group

ΔG_H effect in WTe_2



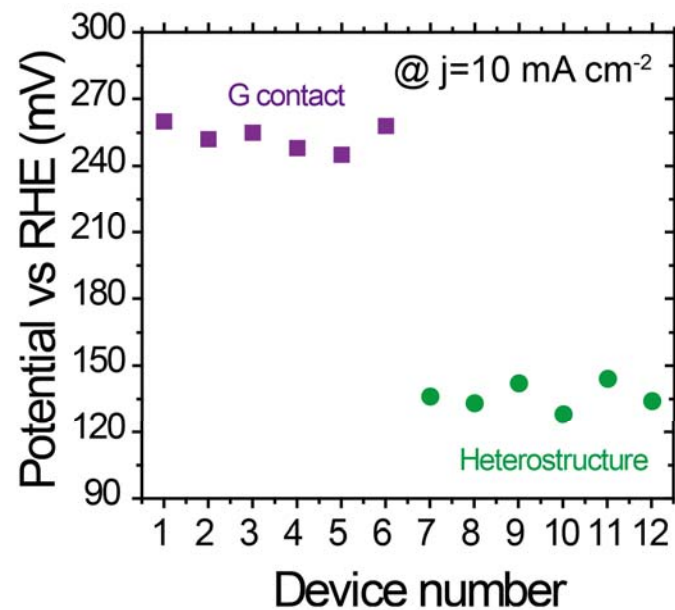
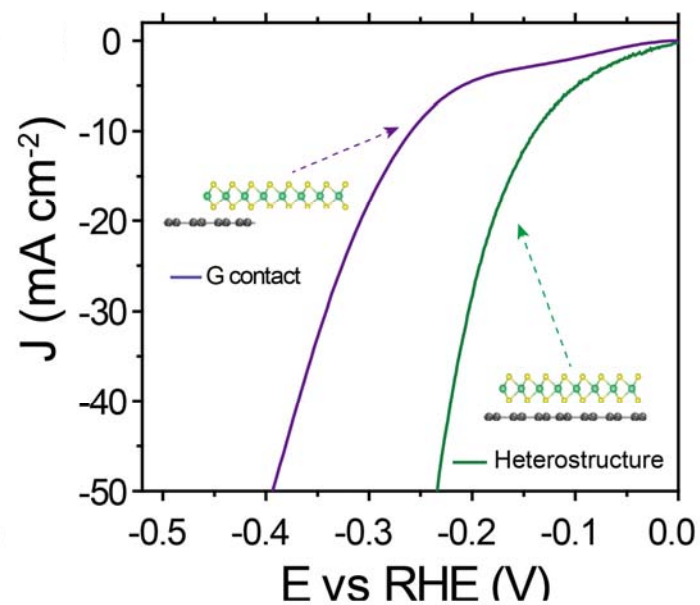
Electron Transport Within Catalyst (σ)

WTe₂: Semimetallic, high electron mobility



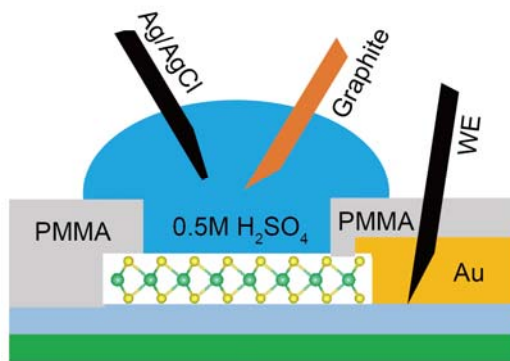
Electron Transport Within Catalyst (σ)

MoS₂: Semiconducting, low electron mobility

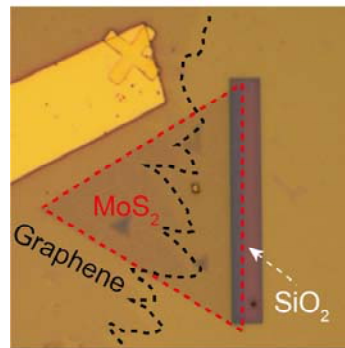
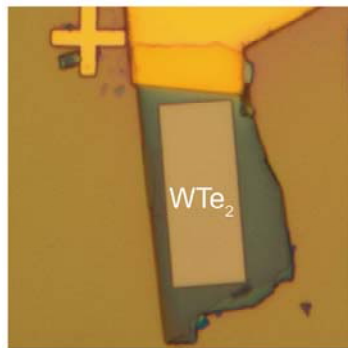


Nanodevice to Unravel HER

- Electrocatalytic reactions are complex
- For HER, ΔG_H , σ , and Φ_{SC} are interdependent



- Types and densities of active sites (ΔG_H)
- Electron transport within catalyst (σ)
- Electron transfer at interface (Φ_{SC})



HER of 2D TMDCs

- Interface barrier as a bottleneck
- Electron transport important
- ΔG_H dependent activity